

A

Bragg's Diffraction Law and X-ray Diffraction

Bragg's Diffraction Condition

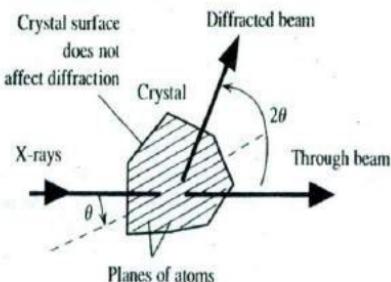
X-rays are electromagnetic (EM) waves with wavelengths typically in the range from 0.01 nm to a few nanometers. This wavelength region is comparable with typical interplanar spacings in crystals. When an X-ray beam impinges on a crystal, the waves in the beam interact with the planes of atoms in the crystal and, as a result, the waves become scattered and the X-ray beam becomes diffracted. An analogy with radio waves may help. Radio waves with wavelengths in the range 1–10 m (short waves and VHF waves) easily interact with objects of comparable size. It is well known that these radio waves become scattered by objects of comparable size such as trees, houses, and buildings. However, long-wave radio waves with wavelengths in kilometers do not become scattered by these objects because the object sizes now are much smaller than the wavelength.

When X-rays strike a crystal, the EM waves penetrate the crystal structure. Each plane of atoms in the crystal reflects a portion of the waves. The reflected waves from different planes then interfere with each other and give rise to a **diffracted beam** which is at a well-defined angle 2θ to the incident beam as depicted in Figure A.1. Some of the incident beam goes through the crystal undiffracted and some of the beam becomes diffracted. Further, the diffracted rays exist only in certain directions. These diffraction directions correspond to well-defined diffraction angles 2θ , as defined in Figure A.1. The diffraction angle 2θ , the wavelength of the X-rays λ , and the interplanar separation d of the diffraction planes within the crystal are related through the **Bragg diffraction condition**, that is,

Bragg's law

$$2d \sin \theta = n\lambda \quad n = 1, 2, 3, \dots \quad [\text{A.1}]$$

Figure A.1 A schematic illustration of X-ray diffraction by a crystal. X-rays penetrate the crystal and then become diffracted by a series of atomic planes.



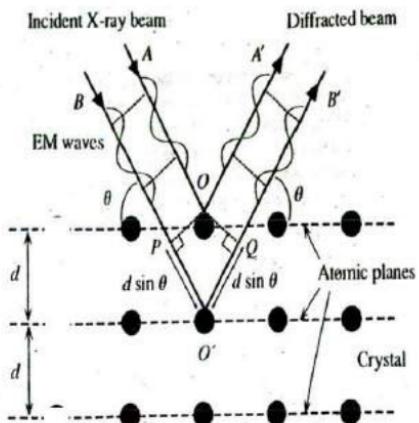


Figure A.2 Diffraction involves X-ray waves being reflected by various atomic planes in the crystal. These waves interfere constructively to form a diffracted beam only for certain diffraction angles that satisfy the Bragg condition.

Consider X-rays penetrating a crystal structure and becoming reflected by a given set of atomic planes as shown in Figure A.2. We can consider an X-ray beam to be many parallel waves that are in phase. These waves penetrate the crystal structure and become reflected at successive atomic planes. The interplanar separation of these planes is d . Waves reflected from adjacent atomic planes interfere constructively to constitute a diffracted beam only when the path difference between the rays is an integer multiple of the wavelength—a requirement of *constructive interference*. This will only be the case for certain directions of reflection. For simplicity, we will consider two waves A and B in an X-ray beam being reflected from two consecutive atomic planes in the crystal. The angle between the X-rays and the atomic planes is θ as defined in Figure A.2. Initially the waves A and B are in phase. Wave A is reflected from the first plane, whereas wave B is reflected from the second plane. When wave A is reflected at O , wave B is at P . Wave B becomes reflected from O' on the second plane and then moves along reflected B' . Wave B has to travel a further distance, $PO'Q$, equivalent to $2d \sin \theta$ before reaching wave A . The path difference between the two reflected waves A' and B' is $PO'Q$ or $2d \sin \theta$. For constructive interference this must be $n\lambda$ where n is an integer. Otherwise the reflected waves will interfere destructively and cancel each other out. Thus the condition for the existence of a diffracted beam is that the path difference between A' and B' should be a multiple of the wavelength λ ; which is Equation A.1. The diffraction condition in Equation A.1 is referred to as Bragg's law. The angle θ is called the Bragg angle, whereas 2θ is called the diffraction angle. The index n is called the order of diffraction. The incidence angle θ is the angle between the incident X-ray and the atomic planes within the crystal and not the angle at the actual crystal surface. The crystal surface, whatever shape, does not affect the diffraction process because X-rays penetrate the crystal and then become diffracted by a series of parallel atomic planes. The Bragg diffraction condition has much wider applications than just crystallography; for example, it is of central importance to the operation of modern semiconductor lasers.

X-ray Diffraction and Study of Crystal Structures

When an X-ray beam is incident on a single crystal, the scattered beam from a given set of planes in the crystal is at an angle 2θ that satisfies the Bragg law. In three dimensions, all directions from the crystal that are at an angle 2θ to the incident beam define a cone as shown in Figure A.3a

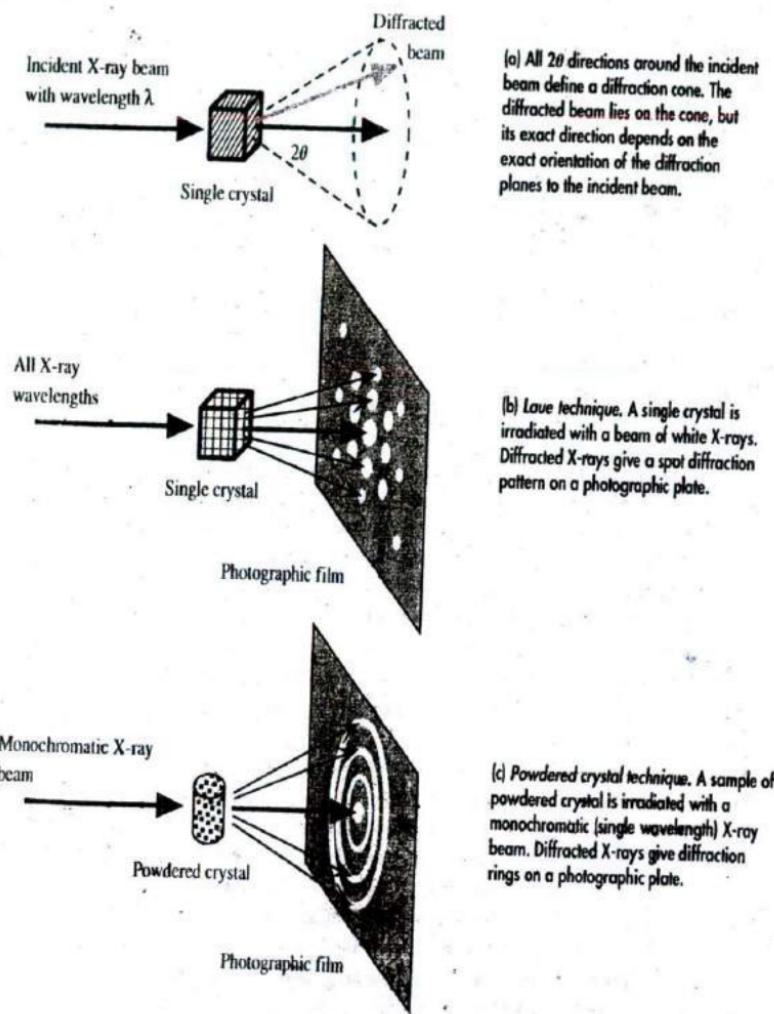


Figure A.3

with its apex at the crystal. This is called a *diffraction cone*. There are many such diffraction cones, each corresponding to a different set of diffraction planes with a distinct set of Miller indices (hkl) . Although all lines lying on a diffraction cone satisfy the Bragg condition, the exact direction of the diffracted beam depends on the exact orientation (or tilt) of the diffracting planes to the incident ray. When a monochromatic X-ray beam is incident on a single crystal, as illustrated in Figure A.3a, the diffracted beam is along one particular direction on the diffraction cone for that set of diffraction planes (hkl) with a particular orientation to the incident beam.

The Laue technique of studying crystal structures involves irradiating a single crystal with a white X-ray beam that has a wide range of wavelengths. A photographic plate is used to capture

the diffraction pattern as shown in Figure A.3b. Effectively we are scanning the wavelength λ and picking up diffractions from various (hkl) planes each time the Bragg condition is satisfied. Thus, whenever λ and d for a particular set of (hkl) planes satisfy the Bragg condition, there is a diffraction. The diffraction pattern is a spot pattern where each spot is the result of diffraction from a given set of (hkl) planes oriented in a particular way to the incident beam. By using a range of wavelengths we ensure that the required wavelength is available for obtaining diffraction for a given set of planes. The relative positions of the spots are used to determine the crystal structure.

One of the simplest methods for studying crystal structures is the powder technique which involves irradiating a powdered crystal, or a polycrystalline sample, with a collimated X-ray beam of known wavelength (monochromatic) as shown in Figure A.3c. Powdering the crystal enables a given set of (hkl) planes to receive the X-rays at many different angles θ and at many different orientations, or tilts. Put differently, it allows the angle θ to be scanned for differently oriented crystals. Since all possible crystal orientations are present by virtue of powdering, the diffracted rays form diffraction cones and the diffraction pattern developed on a photographic plate has *diffraction rings* as shown in Figure A.3c.

Each diffraction ring in the powder technique in Figure A.3c represents diffraction from a given set of (hkl) planes. Whenever the angle θ satisfies the Bragg law for a given set of atomic planes, with Miller indices (hkl) and with an interplanar separation d_{hkl} , there is a diffracted beam. An X-ray detector placed at an angle 2θ with respect to the through-beam will register a peak in the detected X-ray intensity, as shown in Figure A.4a. The instrument that allows this type of X-ray diffraction study is called a *diffractometer*. The variation of the detected intensity with the diffraction angle 2θ represents the diffraction pattern of the crystal. The particular diffraction pattern depicted in Figure A.4b is for aluminum, an FCC crystal. Different crystals exhibit different diffraction patterns.

In the case of cubic crystals, the interplanar spacing d is related to the Miller indices of a plane (hkl) . The separation d_{hkl} between adjacent (hkl) planes is given by

$$d_{hkl} = \frac{a}{\sqrt{h^2 + k^2 + l^2}} \quad [A.2]$$

where a is the lattice parameter (side of the cubic unit cell). When we substitute for $d = d_{hkl}$ in the Bragg condition in Equation A.1, square both sides, and rearrange the equation, we find

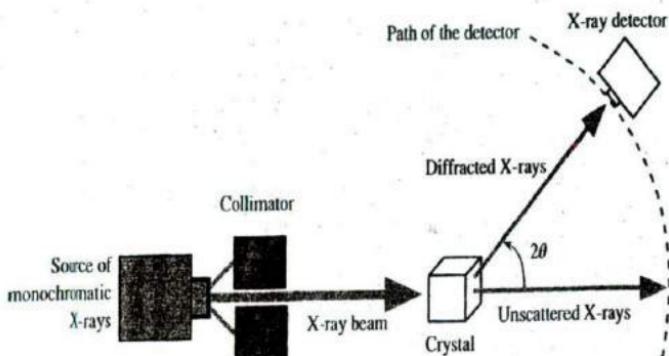
$$(\sin \theta)^2 = \frac{n^2 \lambda^2}{4a^2} (h^2 + k^2 + l^2) \quad [A.3]$$

This is essentially Bragg's law for cubic crystals. The diffraction angle increases with $(h^2 + k^2 + l^2)$. Higher-order Miller indices, those with greater values of $(h^2 + k^2 + l^2)$, give rise to wider diffraction angles. For example, the diffraction angle for (111) is smaller than that for (200) because $(h^2 + k^2 + l^2)$ is 3 for (111) and 4 for (200). Furthermore, with λ and a values that are typically involved in X-ray diffraction, second- and higher-order diffraction peaks, $n = 2, 3, \dots$, can be ruled out.

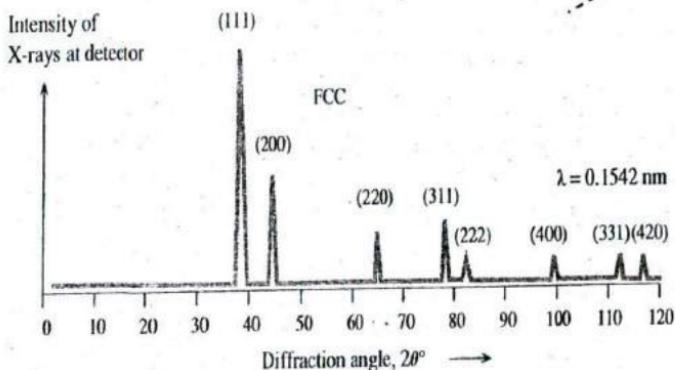
In the case of the simple cubic crystal all possible (hkl) planes give rise to diffraction peaks with diffraction angles satisfying the Bragg law or Equation A.3. The latter equation therefore defines a diffraction pattern for the simple cubic crystal structure because it generates all the possible values of 2θ for all the planes in the cubic crystal. In the case of FCC and BCC crystals, however, not all (hkl) planes give rise to diffraction peaks predicted by Equation A.3. Examination

*Interplanar
separation in
cubic crystals*

*Bragg
condition for
cubic crystals*



(a) A schematic illustration of a diffractometer for X-ray diffraction studies of crystals.



(b) A schematic diagram illustrating the intensity of X-rays as detected in (a) versus the diffraction angle, 2θ , for an FCC crystal (e.g., Al).

Figure A.4 A schematic diagram of a diffractometer and the diffraction pattern obtained from an FCC crystal.

of the diffraction pattern in Figure A.4b for an FCC crystal shows that only those planes with Miller indices that are either all odd or all even integers give rise to diffraction peaks. There are no diffractions from those planes with mixed odd and even integers.

The Bragg law for the cubic crystals in Equation A.3 is a necessary diffraction condition but not sufficient because diffraction involves the interaction of EM waves with the electrons in the crystal. To determine whether there will be a diffraction peak from a set of planes in a crystal we also have to consider the distributions of the atoms and their electrons in the crystal. In FCC and BCC structures diffractions from certain planes are missing because the atoms on these planes give rise to out-of-phase reflections.

B

Flux, Luminous Flux, and the Brightness of Radiation

Many optoelectronic light emitting devices are compared by their luminous efficiencies, which requires a knowledge of photometry. **Radiometry** is the science of radiation measurement, for example, the measurement of emitted, absorbed, reflected, transmitted radiation energy; radiation is understood to mean electromagnetic energy in the optical frequency range (ultraviolet, visible, and infrared). **Photometry**, on the other hand, is a subset of radiometry in which radiation is measured with respect to the spectral responsivity of the eye, that is, over the visible spectrum and by taking into account the spectral visual sensitivity of the eye under normal light adapted conditions, i.e., *photopic* conditions.

Flux (Φ) in radiometry has three related definitions, **radiant**, **luminous** and **photon flux**, which correspond to the rate of flow of radiation energy, perceptible visual energy, and photons, respectively. (Notice that, in radiometry, these fluxes are not defined in terms of flow *per unit area*.) For example, **radiant flux** is the energy flow per unit time in the units of Watts. Radiometric quantities, such as *radiant flux* Φ_e , radiant energy flow per unit time, usually have a subscript *e* and invariably involve energy or power. Radiometric *spectral* quantities, such as *spectral radiant flux* Φ_λ , refer to the radiometric quantity per unit wavelength; i.e., $\Phi_\lambda = d\Phi_e/d\lambda$ is the radiant flux per unit wavelength.

Luminous flux or **photometric flux** Φ_v , is the visual "brightness" of a source as observed by an average daylight adapted eye and is proportional to the radiant flux (radiation power emitted) of the source and the efficiency of the eye to detect the spectrum of the emitted radiation. While the eye can see a red color source, it cannot see an infrared source, and the luminous flux of the infrared source would be zero. Similarly, the eye is less efficient in the violet than in the green region, and less radiant flux is needed to have a green source at the same luminous flux as the blue source. Luminous flux Φ_v is measured in **lumens** (lm), and at a particular wavelength it is given by

$$\Phi_v = \Phi_e \times K \times \eta_{vyc}$$

*Luminous
flux in lumens*

where Φ_e is the radiant flux (in Watts), K is a conversion constant (standardized to be 633 lm/W), η_{vyc} (also denoted as V) is the *luminous efficiency* (*luminous efficacy*) of the daylight adapted eye, which is unity at 555 nm; η_{vyc} depends on the wavelength. By definition, a 1 W light source emitting at 555 nm (green, where $\eta_{vyc} = 1$) emits a luminous flux of 633 lm. The same 1 W light source at 650 nm (red), where $\eta_{vyc} = 0.11$, emits only 70 lm. When we buy a light bulb, we are essentially paying for lumens because it is luminous flux that the eye perceives. A typical 60 W incandescent lamp provides roughly 900 lm. Fluorescent tubes provide more luminous flux

output than incandescent lamps for the same electric power input as they have more spectral emission in the visible region and make better use of the eye's spectral sensitivity. Some examples are 100 W incandescent lamps, 1300–1800 lm, depending on the filament operating temperature (hence bulb design), and 25 W compact fluorescent lamps, 1500–1750 lm.

Luminous efficacy of a light source (such as a lamp) in the lighting industry is the efficiency with which an electric light source converts the input electric power (W) into an emitted luminous flux (lm). A 100 W light bulb producing 1700 lm has an efficacy of 17 lm/W. While at present the LED efficacies are below those of fluorescent tubes, rapid advances in LED technologies are bringing the expected efficacies to around 50 lm/W or higher. LEDs as solid-state lamps have much longer lifetimes and much higher reliability, and hence are expected to be more economical than incandescent and fluorescent lamps.



From left to right: Michael Faraday, Thomas Henry Huxley, Charles Wheatstone, David Brewster and John Tyndall. Professor Tyndall has been attributed with the first demonstration [1854] of light being guided along a water jet, which is based in total internal reflection.

[SOURCE: Courtesy of AIP Emilio Segrè Visual Archives, Zeleny Collection.]

d (subscript)	donor, e.g., N_d = donor concentration (m^{-3})
dc	direct current
d_{ij}	piezoelectric coefficients
E	energy; electric field (V m^{-1}) (Ch. 9)
E_a, E_d	acceptor and donor energy levels
E_c, E_v	conduction band edge, valence band edge
E_{ex}	exchange interaction energy
E_F, E_{FO}	Fermi energy, Fermi energy at 0 K
E_g	bandgap energy
E_{mag}	magnetic energy
E	electric field (V m^{-1})
E_{br}	dielectric strength or breakdown field (V m^{-1})
E_{loc}	local electric field
e	electronic charge ($1.602 \times 10^{-19} \text{ C}$)
e (subscript)	electron, e.g., μ_e = electron drift mobility; electronic
eff (subscript)	effective, e.g., μ_{eff} = effective drift mobility
EHP	electron-hole pair
EM	electromagnetic
EMF (emf)	electromagnetic force (V)
F	force (N); function
f	frequency; function
$f(E)$	Fermi-Dirac function
FCC	face-centered cubic
FET	field effect transistor
G	rate of generation
G_{ph}	rate of photogeneration
G_p	parallel conductance (Ω^{-1})
$g(E)$	density of states
g	conductance; transconductance (A/V); piezoelectric voltage coefficient (Ch. 7)
g_d	incremental or dynamic conductance (A/V)
g_m	mutual transconductance (A/V)
H, H	magnetic field intensity (strength), magnetizing field (A m^{-1})
h	Planck's constant ($6.6261 \times 10^{-34} \text{ J s}$)
\hbar	Planck's constant divided by 2π ($\hbar = 1.0546 \times 10^{-34} \text{ J s}$)
h (subscript)	hole, e.g., μ_h = hole drift mobility
h_{FE}, h_f	dc current gain, small-signal (ac) current gain in the common emitter configuration
HCP	hexagonal close-packed
HF	high frequency
I	electric current (A); moment of inertia (kg m^2) (Ch. 1)
I	light intensity (W m^{-2})
I, i (subscript)	quantity related to ionic polarization
I_{br}	breakdown current
I_B, I_C, I_E	base, collector, and emitter currents in a BJT

C

Major Symbols and Abbreviations

<i>A</i>	area; cross-sectional area; amplification
<i>a</i>	lattice parameter; acceleration; amplitude of vibrations; half-channel thickness in a JFET (Ch. 6)
<i>a</i> (subscript)	acceptor, e.g., N_a = acceptor concentration (m^{-3})
<i>ac</i>	alternating current
<i>a_B</i>	Bohr radius (0.0529 nm)
<i>A_V, A_P</i>	voltage amplification, power amplification
<i>APF</i>	atomic packing factor
<i>B, B</i>	magnetic field vector (T), magnetic field
<i>B</i>	frequency bandwidth
<i>B_c</i>	critical magnetic field
<i>B_m</i>	maximum magnetic field
<i>B₀, B_e</i>	Richardson-Dushman constant, effective Richardson-Dushman constant
<i>BC</i>	base collector
<i>BCC</i>	body-centered cubic
<i>BE</i>	base emitter
<i>BJT</i>	bipolar junction transistor
<i>C</i>	capacitance; composition; the Nordheim coefficient ($\Omega \text{ m}$)
<i>c</i>	speed of light ($3 \times 10^8 \text{ m s}^{-1}$); specific heat capacity ($\text{J K}^{-1} \text{ kg}^{-1}$)
<i>C_{dpl}</i>	depletion layer capacitance
<i>C_m</i>	molar heat capacity ($\text{J K}^{-1} \text{ mol}^{-1}$)
<i>C_{diff}</i>	diffusion (storage) capacitance of a forward-biased <i>pn</i> junction
<i>c_v</i>	specific heat capacity ($\text{J K}^{-1} \text{ kg}^{-1}$)
<i>C_v</i>	heat capacity per unit volume ($\text{J K}^{-1} \text{ m}^{-3}$)
<i>CB</i>	conduction band; common base
<i>CE</i>	common emitter
<i>CMOS</i>	complementary MOS
<i>CN</i>	coordination number
<i>CVD</i>	chemical vapor deposition
<i>D</i>	diffusion coefficient ($\text{m}^2 \text{ s}^{-1}$); thickness; electric displacement (C m^{-2})
<i>d</i>	density (kg m^{-3}); distance; separation of the atomic planes in a crystal, separation of capacitor plates; piezoelectric coefficient; mean grain size (Ch. 2)

<i>i</i>	instantaneous current (A); small-signal (ac) current, $i = \delta I$
<i>i</i> (subscript)	intrinsic, e.g., n_i = intrinsic concentration
i_b, i_c, i_e	small signal base, collector, and emitter currents ($\delta I_B, \delta I_C, \delta I_E$) in a BJT
IC	integrated circuit
<i>J</i>	current density (A m^{-2})
\mathbf{J}	total angular momentum vector
<i>j</i>	imaginary constant: $\sqrt{-1}$
J_c	critical current density (A m^{-2})
J_p	pyroelectric current density
JFET	junction FET
<i>K</i>	spring constant (Ch. 1); phonon wavevector (m^{-1}); bulk modulus (Pa); dielectric constant (Ch. 7)
<i>k</i>	Boltzmann constant ($k = R/N_A = 1.3807 \times 10^{-23} \text{ J K}^{-1}$); wavenumber ($k = 2\pi/\lambda$), wavevector (m^{-1}); electromechanical coupling factor (Ch. 7)
KE	kinetic energy
L	total orbital angular momentum
<i>L</i>	length; inductance
<i>t</i>	length; mean free path; orbital angular momentum quantum number
L_{ch}	channel length in a FET
L_e, L_h	electron and hole diffusion lengths
ℓ_s, ℓ_p	lengths of the <i>n</i> - and <i>p</i> -regions outside depletion region in a <i>pn</i> junction
$\ln(x)$	natural logarithm of <i>x</i>
LCAO	linear combination of atomic orbitals
M, M'	magnetization vector (A m^{-1}), magnetization (A m^{-1})
<i>M</i>	multiplication in avalanche effect
M_A	relative atomic mass; atomic mass; "atomic weight" (g mol^{-1})
M_r	remanent or residual magnetization (A m^{-1}); reduced mass of two bodies <i>A</i> and <i>B</i> , $M_r = M_A M_B / (M_A + M_B)$
M_{sat}	saturation magnetization (A m^{-1})
<i>m</i>	mass (kg)
m_e	mass of the electron in free space ($9.10939 \times 10^{-31} \text{ kg}$)
m_e^*	effective mass of the electron in a crystal
m_h^*	effective mass of a hole in a crystal
m_l	magnetic quantum number
m_s	spin magnetic quantum number
MOS (MOST)	metal-oxide-semiconductor (transistor)
MOSFET	metal-oxide-semiconductor FET
<i>N</i>	number of atoms or molecules; number of atoms per unit volume (m^{-3}) (Chs. 7 and 9); number of turns on a coil (Ch. 8)
N_A	Avogadro's number ($6.022 \times 10^{23} \text{ mol}^{-1}$)
<i>n</i>	electron concentration (number per unit volume); atomic concentration; principal quantum number; integer number; refractive index (Ch. 9)
n^+	heavily doped <i>n</i> -region
n_{st}	number of atoms per unit volume

N_c, N_v	effective density of states at the conduction and valence band edges (m^{-3})
N_d, N_i^+	donor and ionized donor concentrations (m^{-3})
n_e, n_o	refractive index for extraordinary and ordinary waves in a birefringent crystal
n_i	intrinsic concentration (m^{-3})
n_{no}, p_{pe}	equilibrium majority carrier concentrations (m^{-3})
n_{po}, p_{ne}	equilibrium minority carrier concentrations (m^{-3})
N_s	concentration of electron scattering centers
n_u	velocity density function; vacancy concentration (m^{-3})
P	probability; pressure (Pa); power (W) or power loss (W)
\mathbf{p}, \mathbf{p}	electric dipole moment (C m)
p	hole concentration (m^{-3}); momentum ($kg\ m\ s^{-1}$); pyroelectric coefficient ($C\ m^{-2}\ K^{-1}$) (Ch. 7)
p^+	heavily doped p -region
p_{av}	average dipole moment per molecule
p_e	electron momentum ($kg\ m\ s^{-1}$)
PE	potential energy
$p_{induced}$	induced dipole moment (C m)
p_o	permanent dipole moment (C m)
PET	polyester, polyethylene terephthalate
PZT	lead zirconate titanate
Q	charge (C); heat (J); quality factor
Q'	rate of heat flow (W)
q	charge (C); an integer number used in lattice vibrations (Ch. 4)
R	gas constant ($N_A k = 8.3145\ J\ mol^{-1}\ K^{-1}$); resistance; radius; reflection coefficient (Ch. 3); rate of recombination (Ch. 5)
R	reflectance (Ch. 9)
$\mathcal{R}_b, \mathcal{R}_v$	pyroelectric current and voltage responsivities
\mathbf{r}	position vector
r	radial distance; radius; interatomic separation; resistance per unit length
r	reflection coefficient (Ch. 9)
R_H	Hall coefficient ($m^3\ C^{-1}$)
r_o	bond length, equilibrium separation
rms	root mean square
S	total spin momentum, intrinsic angular momentum; Poynting vector (Ch. 9)
S	cross-sectional area of a scattering center; Seebeck coefficient, thermoelectric power ($V\ m^{-1}$); strain (Ch. 7)
S_{band}	number of states per unit volume in the band
S_j	strain along direction j
SCL	space charge layer
T	temperature in Kelvin; transmission coefficient
T	transmittance
t	time (s); thickness (m)
t	transmission coefficient
$\tan \delta$	loss tangent

T_C	Curie temperature
T_c	critical temperature (K)
T_j	mechanical stress along direction j (Pa)
TC	thermocouple
TCC	temperature coefficient of capacitance (K^{-1})
TCR	temperature coefficient of resistivity (K^{-1})
U	total internal energy
u	mean speed (of electron) ($m s^{-1}$)
V	voltage; volume; PE function of the electron, $PE(x)$
V_{bc}	breakdown voltage
V_o	built-in voltage
V_p	pinch-off voltage
V_r	reverse bias voltage
$\frac{v}{v^2}$	velocity ($m s^{-1}$); instantaneous voltage (V)
v_{dx}	mean square velocity; mean square voltage
v_e, v_{rms}	drift velocity in the x direction
v_F	effective velocity or rms velocity of the electron
v_g, v_g	Fermi speed
v_h	group velocity
VB	thermal velocity
W	valence band
W_o	width; width of depletion layer with applied voltage; dielectric loss
W_n, W_p	width of depletion region with no applied voltage
	width of depletion region on the n -side and on the p -side with no applied voltage
X	atomic fraction
Y	admittance (Ω^{-1}); Young's modulus (Pa)
Z	impedance (Ω); atomic number, number of electrons in the atom
α	polarizability; temperature coefficient of resistivity (K^{-1}); absorption coefficient (m^{-1}); gain or current transfer ratio from emitter to collector of a BJT
β	current gain I_C/I_B of a BJT; Bohr magneton ($9.2740 \times 10^{-24} J T^{-1}$); spring constant (Ch. 4)
β_s	Schottky coefficient
γ	emitter injection efficiency (Ch. 6); gyromagnetic ratio (Ch. 8); Grüneisen parameter (Ch. 4); loss coefficient in the Lorentz oscillator model
Γ, Γ_{ph}	flux ($m^{-2} s^{-1}$), photon flux (photons $m^{-2} s^{-1}$)
δ	small change; skin depth (Ch. 2); loss angle (Ch. 7); domain wall thickness (Ch. 8); penetration depth (Ch. 9)
Δ	change, excess (e.g., $\Delta n =$ excess electron concentration)
∇^2	$\partial^2/\partial x^2 + \partial^2/\partial y^2 + \partial^2/\partial z^2$
ϵ	$\epsilon_o \epsilon_r$, permittivity of a medium ($C V^{-1} m^{-1}$ or $F m^{-1}$); elastic strain
ϵ_0	permittivity of free space or absolute permittivity ($8.8542 \times 10^{-12} C V^{-1} m^{-1}$ or $F m^{-1}$)

ϵ_r	relative permittivity or dielectric constant
η	efficiency; quantum efficiency; ideality factor
θ	angle; an angular spherical coordinate; thermal resistance; angle between a light ray and normal to a surface (Ch. 9)
κ	thermal conductivity ($\text{W m}^{-1} \text{K}^{-1}$); dielectric constant
λ	wavelength (m); thermal coefficient of linear expansion (K^{-1}); electron mean free path in the bulk crystal (Ch. 2); characteristic length (Ch. 8)
μ, μ	magnetic dipole moment (A m^2) (Ch. 3)
μ	$\mu_0\mu_r$, magnetic permeability (H m^{-1}); chemical potential (Ch. 5)
μ_o	absolute permeability ($4\pi \times 10^{-7} \text{ H m}^{-1}$)
μ_r	relative permeability
μ_m, μ_m	magnetic dipole moment (A m^2) (Ch. 8)
μ_d	drift mobility ($\text{m}^2 \text{ V}^{-1} \text{ s}^{-1}$)
μ_h, μ_e	hole drift mobility, electron drift mobility ($\text{m}^2 \text{ V}^{-1} \text{ s}^{-1}$)
v	frequency (Hz); Poisson's ratio; volume fraction (Ch. 7)
π	pi, $3.14159\dots$; piezoresistive coefficient (Pa^{-1})
π_L, π_T	longitudinal and transverse piezoresistive coefficients (Pa^{-1})
Π	Peltier coefficient (V)
ρ	resistivity ($\Omega \text{ m}$); density (kg m^{-3}); charge density (C m^{-3})
ρ_E	energy density (J m^{-3})
ρ_{net}	net space charge density (C m^{-3})
ρJ^2	Joule heating per unit volume (W m^{-3})
σ	electrical conductivity ($\Omega^{-1} \text{ m}^{-1}$); surface concentration of charge (C m^{-2}) (Ch. 7)
σ_p	polarization charge density (C m^{-2})
σ_o	free surface charge density (C m^{-2})
σ_S	Stefan's constant ($5.670 \times 10^{-8} \text{ W m}^{-2} \text{ K}^{-4}$)
τ	time constant; mean electron scattering time; relaxation time; torque (N m)
τ_g	mean time to generate an electron-hole pair
ϕ	angle; an angular spherical coordinate
Φ	work function (J or eV), magnetic flux (Wb)
Φ_e	radiant flux (W)
Φ_m	metal work function (J or eV)
Φ_n	energy required to remove an electron from an <i>n</i> -type semiconductor (J or eV)
Φ_v	luminous flux (lumens)
X	volume fraction; electron affinity; susceptibility (χ_e is electrical; χ_m is magnetic)
$\Psi(x, t)$	total wavefunction
$\psi(x)$	spatial dependence of the electron wavefunction under steady-state conditions
$\psi_k(x)$	Bloch wavefunction, electron wavefunction in a crystal
ψ_{hyb}	hybrid orbital
ω	angular frequency ($2\pi v$); oscillation frequency (rad s^{-1})
ω_I	ionic polarization resonance frequency (angular)
ω_o	resonance or natural frequency (angular) of an oscillating system.

Element	Symbol	Z	Atomic Mass (g mol ⁻¹)	Electronic Structure	Density (g cm ⁻³) (*at 0 °C, 1 atm)	Crystal in Solid State
Arsenic	As	33	74.92	[Ar]3d ¹⁰ 4s ² p ³	5.72	Rhombohedral
Selenium	Se	34	78.96	[Ar]3d ¹⁰ 4s ² p ⁴	4.80	Hexagonal
Bromine	Br	35	79.90	[Ar]3d ¹⁰ 4s ² p ⁵	3.12	Orthorhombic
Krypton	Kr	36	83.80	[Ar]3d ¹⁰ 4s ² p ⁶	3.74	FCC
Rubidium	Rb	37	85.47	[Kr]5s ¹	1.53	BCC
Strontium	Sr	38	87.62	[Kr]5s ²	2.6	FCC
Yttrium	Y	39	88.90	[Kr]4d ¹ 5s ²	4.5	HCP
Zirconium	Zr	40	91.22	[Kr]4d ² 5s ²	6.50	HCP
Niobium	Nb	41	92.91	[Kr]4d ⁴ 5s ¹	8.55	BCC
Molybdenum	Mo	42	95.94	[Kr]4d ⁵ 5s ¹	10.2	BCC
Technetium	Tc	43	(97.91)	[Kr]4d ⁵ 5s ²	11.5	HCP
Ruthenium	Ru	44	101.07	[Kr]4d ⁷ 5s ¹	12.2	HCP
Rhodium	Rh	45	102.91	[Kr]4d ⁸ 5s ¹	12.4	FCC
Palladium	Pd	46	106.42	[Kr]4d ¹⁰	12.0	FCC
Silver	Ag	47	107.87	[Kr]4d ¹⁰ 5s ¹	10.5	FCC
Cadmium	Cd	48	112.41	[Kr]4d ¹⁰ 5s ²	8.65	HCP
Indium	In	49	114.82	[Kr]4d ¹⁰ 5s ² p ¹	7.31	FCT
Tin	Sn	50	118.71	[Kr]4d ¹⁰ 5s ² p ²	7.30	BCT
Antimony	Sb	51	121.75	[Kr]4d ¹⁰ 5s ² p ³	6.68	Rhombohedral
Tellurium	Te	52	127.60	[Kr]4d ¹⁰ 5s ² p ⁴	6.24	Hexagonal
Iodine	I	53	126.91	[Kr]4d ¹⁰ 5s ² p ⁵	4.92	Orthorhombic
Xenon	Xe	54	131.29	[Kr]4d ¹⁰ 5s ² p ⁶	0.0059*	FCC
Cesium	Cs	55	132.90	[Xe]6s ¹	1.87	BCC
Barium	Ba	56	137.33	[Xe]6s ²	3.62	BCC
Lanthanum	La	57	138.91	[Xe]5d ¹ 6s ²	6.15	HCP
Cerium	Ce	58	140.12	[Xe]4f ¹ 5d ¹ 6s ²	6.77	FCC
Praseodymium	Pr	59	140.91	[Xe]4f ³ 6s ²	6.77	HCP
Neodymium	Nd	60	144.24	[Xe]4f ⁴ 6s ²	7.00	HCP
Promethium	Pm	61	(145)	[Xe]4f ⁵ 6s ²	7.26	Hexagonal
Samarium	Sm	62	150.4	[Xe]4f ⁶ 6s ²	7.5	Rhombohedral
Europium	Eu	63	151.97	[Xe]4f ⁷ 6s ²	5.24	BCC
Gadolinium	Gd	64	157.25	[Xe]4f ⁷ 5d ¹ 6s ²	7.90	HCP
Terbium	Tb	65	158.92	[Xe]4f ⁹ 6s ²	8.22	HCP
Dysprosium	Dy	66	162.50	[Xe]4f ¹⁰ 6s ²	8.55	HCP
Holmium	Ho	67	164.93	[Xe]4f ¹¹ 6s ²	8.80	HCP
Erbium	Er	68	167.26	[Xe]4f ¹² 6s ²	9.06	HCP
Thulium	Tm	69	168.93	[Xe]4f ¹³ 6s ²	9.32	HCP
Ytterbium	Yb	70	173.04	[Xe]4f ¹⁴ 6s ²	6.90	FCC
Lutetium	Lu	71	174.97	[Xe]4f ¹⁴ 5d ¹ 6s ²	9.84	HCP
Hafnium	Hf	72	178.49	[Xe]4f ¹⁴ 5d ² 6s ²	13.3	HCP
Tantalum	Ta	73	180.95	[Xe]4f ¹⁴ 5d ³ 6s ²	16.4	BCC
Tungsten	W	74	183.84	[Xe]4f ¹⁴ 5d ⁴ 6s ²	19.3	BCC
Rhenium	Re	75	186.21	[Xe]4f ¹⁴ 5d ⁵ 6s ²	21.0	HCP

D

Elements to Uranium

Element	Symbol	Z	Atomic Mass (g mol ⁻¹)	Electronic Structure	Density (g cm ⁻³) (*at 0 °C, 1 atm)	Crystal in Solid State
Hydrogen	H	1	1.008	1s ¹	0.00009*	HCP
Helium	He	2	4.003	1s ²	0.00018*	FCP
Lithium	Li	3	6.941	[He]2s ¹	0.54	BCC
Beryllium	Be	4	9.012	[He]2s ²	1.85	HCP
Boron	B	5	10.81	[He]2s ² p ¹	2.5	Rhombohedral
Carbon	C	6	12.01	[He]2s ² p ²	2.3	Hexagonal
Nitrogen	N	7	14.007	[He]2s ² p ³	0.00125*	HCP
Oxygen	O	8	16.00	[He]2s ² p ⁴	0.00143*	Monoclinic
Fluorine	F	9	18.99	[He]2s ² p ⁵	0.00170*	Monoclinic
Neon	Ne	10	20.18	[He]2s ² p ⁶	0.00090*	FCC
Sodium	Na	11	22.99	[Ne]3s ¹	0.97	BCC
Magnesium	Mg	12	24.31	[Ne]3s ²	1.74	HCP
Aluminum	Al	13	26.98	[Ne]3s ² p ¹	2.70	FCC
Silicon	Si	14	28.09	[Ne]3s ² p ²	2.33	Diamond
Phosphorus	P	15	30.97	[Ne]3s ² p ³	1.82	Triclinic
Sulfur	S	16	32.06	[Ne]3s ² p ⁴	2.0	Orthorhombic
Chlorine	Cl	17	35.45	[Ne]3s ² p ⁵	0.0032*	Orthorhombic
Argon	Ar	18	39.95	[Ne]3s ² p ⁶	0.0018*	FCC
Potassium	K	19	39.09	[Ar]4s ¹	0.86	BCC
Calcium	Ca	20	40.08	[Ar]4s ²	1.55	FCC
Scandium	Sc	21	44.96	[Ar]3d ¹ 4s ²	3.0	HCP
Titanium	Ti	22	47.87	[Ar]3d ² 4s ²	4.5	HCP
Vanadium	V	23	50.94	[Ar]3d ³ 4s ²	5.8	BCC
Chromium	Cr	24	52.00	[Ar]3d ⁵ 4s ¹	7.19	BCC
Manganese	Mn	25	54.95	[Ar]3d ⁵ 4s ²	7.43	BCC
Iron	Fe	26	55.85	[Ar]3d ⁶ 4s ²	7.86	BCC
Cobalt	Co	27	58.93	[Ar]3d ⁷ 4s ²	8.90	HCP
Nickel	Ni	28	58.69	[Ar]3d ⁸ 4s ²	8.90	FCC
Copper	Cu	29	63.55	[Ar]3d ¹⁰ 4s ¹	8.96	FCC
Zinc	Zn	30	65.39	[Ar]3d ¹⁰ 4s ²	7.14	HCP
Gallium	Ga	31	69.72	[Ar]3d ¹⁰ 4s ² p ¹	5.91	Orthorhombic
Germanium	Ge	32	72.61	[Ar]3d ¹⁰ 4s ² p ²	5.32	Diamond

Element	Symbol	Z	Atomic mass (g mol ⁻¹)	Electronic Structure	Density (g cm ⁻³) (*at 0 °C, 1 atm)	Crystal in Solid State
Osmium	Os	76	190.2	[Xe]4f ¹⁴ 5d ⁶ 6s ²	22.6	HCP
Iridium	Ir	77	192.22	[Xe]4f ¹⁴ 5d ⁶ 6s ²	22.5	FCC
Platinum	Pt	78	195.08	[Xe]4f ¹⁴ 5d ⁶ 6s ¹	21.4	FCC
Gold	Au	79	196.97	[Xe]4f ¹⁴ 5d ¹⁰ 6s ¹	19.3	FCC
Mercury	Hg	80	200.59	[Xe]4f ¹⁴ 5d ¹⁰ 6s ²	13.55	Rhombohedral
Thallium	Tl	81	204.38	[Xe]4f ¹⁴ 5d ¹⁰ 6s ² p ¹	11.8	HCP
Lead	Pb	82	207.2	[Xe]4f ¹⁴ 5d ¹⁰ 6s ² p ²	11.34	FCC
Bismuth	Bi	83	208.98	[Xe]4f ¹⁴ 5d ¹⁰ 6s ² p ³	9.8	Rhombohedral
Polonium	Po	84	(209)	[Xe]4f ¹⁴ 5d ¹⁰ 6s ² p ⁴	9.2	SC
Astatine	At	85	(210)	[Xe]4f ¹⁴ 5d ¹⁰ 6s ² p ⁵	—	Rhombohedral
Radon	Rn	86	(222)	[Xe]4f ¹⁴ 5d ¹⁰ 6s ² p ⁶	0.0099*	—
Francium	Fr	87	(223)	[Rn]7s ¹	—	—
Radium	Ra	88	226.02	[Rn]7s ²	5	BCC
Actinium	Ac	89	227.02	[Rn]6d ¹ 7s ²	10.0	FCC
Thorium	Th	90	232.04	[Rn]6d ² 7s ²	11.7	FCC
Protactinium	Pa	91	(231.03)	[Rn]5f ² 6d ¹ 7s ²	15.4	BCT
Uranium	U	92	(238.05)	[Rn]5f ³ 6d ¹ 7s ²	19.07	Orthorhombic



"I don't really start until I get my proofs back from the printers. Then I can begin serious writing."

John Maynard Keynes (1883–1946)

E**Constants and Useful Information****Physical Constants**

Atomic mass unit	amu	$1.66054 \times 10^{-27} \text{ kg}$
Avogadro's number	N_A	$6.02214 \times 10^{23} \text{ mol}^{-1}$
Bohr magneton	β	$9.2740 \times 10^{-24} \text{ JT}^{-1}$
Boltzmann constant	k	$1.3807 \times 10^{-23} \text{ J K}^{-1} = 8.6174 \times 10^{-5} \text{ eV K}^{-1}$
Electron mass in free space	m_e	$9.10939 \times 10^{-31} \text{ kg}$
Electron charge	e	$1.60218 \times 10^{-19} \text{ C}$
Gas constant	R	$8.3145 \text{ J K}^{-1} \text{ mol}^{-1}$ or $\text{m}^3 \text{ Pa K}^{-1} \text{ mol}^{-1}$
Gravitational constant	G	$6.6742 \times 10^{-11} \text{ N m}^2 \text{ kg}^{-2}$
Permeability of vacuum or absolute permeability	μ_0	$4\pi \times 10^{-7} \text{ H m}^{-1}$ (or $\text{Wb A}^{-1} \text{ m}^{-1}$)
Permittivity of vacuum or absolute permittivity	ϵ_0	$8.8542 \times 10^{-12} \text{ F m}^{-1}$
Planck's constant	h	$6.626 \times 10^{-34} \text{ J s} = 4.136 \times 10^{-15} \text{ eV s}$
Planck's constant/ 2π	\hbar	$1.055 \times 10^{-34} \text{ J s} = 6.582 \times 10^{-16} \text{ eV s}$
Proton rest mass	m_p	$1.67262 \times 10^{-27} \text{ kg}$
Rydberg constant	R_∞	$1.0974 \times 10^7 \text{ m}^{-1}$
Speed of light	c	$2.9979 \times 10^8 \text{ m s}^{-1}$
Stefan's constant	σ_s	$5.6704 \times 10^{-8} \text{ W m}^{-2} \text{ K}^{-4}$

Useful Information

Acceleration due to gravity at 45° latitude	g	9.81 m s^{-2}
kT at $T = 293 \text{ K}$ (20°C)	kT	0.02525 eV
kT at $T = 300 \text{ K}$ (27°C)	kT	0.02585 eV
Bohr radius	a_0	0.0529 nm
1 angstrom	\AA	10^{-10} m
1 micron	μm	10^{-6} m
1 eV = $1.6022 \times 10^{-19} \text{ J}$		
1 kJ mol $^{-1}$ = $0.010364 \text{ eV atom}^{-1}$		
1 atmosphere (pressure)		
= $1.013 \times 10^5 \text{ Pa}$		

LED Colors

The table gives the wavelength ranges and colors as usually specified for LEDs.

Color	Blue	Emerald green	Green	Yellow	Amber	Orange	Red orange	Red	Deep red	Infrared
$\lambda \text{ (nm)}$	$\lambda < 500$	530–564	565–579	580–587	588–594	595–606	607–615	616–632	633–700	$\lambda > 700$

Visible Spectrum

The table gives the typical wavelength ranges and color perception by an average person.

Color	Violet	Blue	Green	Yellow	Orange	Red
$\lambda \text{ (nm)}$	390–455	435–492	492–577	577–597	597–622	622–780

Complex Numbers

$$j = (-1)^{1/2} \quad j^2 = -1$$

$$\exp(j\theta) = \cos\theta + j\sin\theta$$

$$Z = a + jb = re^{j\theta} \quad r = (a^2 + b^2)^{1/2} \quad \tan\theta = \frac{b}{a}$$

$$Z^* = a - jb = re^{-j\theta} \quad \operatorname{Re}(Z) = a \quad \operatorname{Im}(Z) = b$$

$$\text{Magnitude}^2 = |Z|^2 = ZZ^* = a^2 + b^2 \quad \text{Argument} = \theta = \arctan\left(\frac{b}{a}\right)$$

$$\cos\theta = \frac{1}{2}(e^{j\theta} + e^{-j\theta}) \quad \sin\theta = \frac{1}{2j}(e^{j\theta} - e^{-j\theta})$$

Expansions

$$e^x = 1 + x + \frac{1}{2!}x^2 + \frac{1}{3!}x^3 + \dots$$

$$(1+x)^n = 1 + nx + \frac{n(n-1)}{2!}x^2 + \frac{n(n-1)(n-2)}{3!}x^3 + \dots$$

$$\text{Small } x: \quad (1+x)^n \approx 1 + nx \quad \sin x \approx x \quad \tan x \approx x \quad \cos x \approx 1$$

$$\text{Small } \Delta x \text{ in } x = x_0 + \Delta x: \quad f(x) \approx f(x_0) + \Delta x \left(\frac{df}{dx} \right)_{x_0}$$

index

- Accelerated failure tests, 177
Acceptors, 390, 461
Accumulation, 570
Accumulation region, 444
Activated static, 98
Activation energy, 98
Activator, 120, 841
excitation, 822
Active device, defined, 570
Affinity, electron, 375, 386, 462
Allotropy, 61–43, 102
transition temperature, 61
Alloy, 178
ternary, iii–v, 545
Amorphous semiconductors, 78–82,
458–461
bandgap, 460
extended states, 458, 462
localized states, 459, 463
mobility edge, 460
tail states, 460
Amorphous solids, 78–82, 98–99
Ampere's law, 693
Angular momentum, 269
intrinsic, 245–247
orbital, 232
potential energy, 249–250
total, 252–253
Anion, 6, 15, 99
Anisotropic magnetoresistance (AMR),
744–748, 762
Anisotropy, magnetocrystalline, 706–708
shape, 725, 763
Antibonding orbital, 286, 288
Antiferromagnetism, 699, 759
Antireflection coating, 570, 802–803
Arrhenius rate equation, 47
a-Si:H, 82, 459
Aspect ratio, 175
Atomic concentration, 55
Atomic mass, 8
Atomic mass number, 8
Atomic mass units (amu), 8, 99
Atomic number, 4
effective (Z_{eff}), 240
Atomic packing factor (APF), 55, 99
Atomic structure, 3–8
orbital angular momentum quantum
number, 4, 232, 270
principal quantum number, 4, 232, 270
shell, 4, 239
subshells, 4, 239
Atomic weight, See Atomic mass
Attenuation, 841
Attenuation coefficient, 841
Attenuation in optical fibers, 817–819
graph, 818
Rayleigh scattering limit, 819
Avalanche breakdown, 502–504, 570
Avalanche effect, 503
Average free time (in electron drift), 117.
See also Mean free time
Avogadro's number, 8, 25, 99
B versus *H*, 716–717
Balmer series, 278
Bathurst–Rydberg formula, 245
Band theory of solids, 291–299
Bandgap (energy gap) E_g , 302, 355, 357,
375, 464
direct band gap, 430, 451
indirect band gap, 430, 452
mobility gap, 460
narrowing and emitter injection
efficiency, 576
temperature dependence, 467
Bardeen–Cooper–Schrieffer
photo, 731
theory, 739
Barkhausen effect, 715
Basis, 50, 95, 99
BCC (body centered cubic). *See* Crystal
structure
BCS theory. *See* Bardeen–Cooper–
Schrieffer
BCT (body centered tetragonal). *See*
Crystal structure
Bednorz, J., George, 684
Beer–Lambert law, 428
Biaxial crystals, 828
negative, 828
positive, 828
Binary eutectic phase diagrams, 90–95
Bipolar junction transistor, 475, 506–522,
570
 α , 509–510
active region, 511
amplifier, CB, 515–517
 β , 510, 521
base, 506
base transport factor, α_B , 509–510
base–grid modulation, 512, 570. *See*
also Early effect
collector, 506
collector junction, 507, 570
common base (CB) configuration,
506–517
common emitter (CE) DC characteris-
tics, 517–518
current gain α , CB, 509–510
current transfer ratio β , 509, 514
emitter, 506
emitter injection efficiency, 513–514,
573
emitter junction, 507, 571
emitter current, 509
equations, *pop* BJT, 574–575
input resistance, 516, 519
power gain, 509
saturated operating region, 518
small signal equivalent circuit, 572
small signal low-frequency model,
518–522
transconductance, 520
transistor action, 509
transit time, minority carrier, 510
voltage gain, 516, 520
Birefringence. *See also* Retarding plates
circular, 835–837
crystals, 827, 841
of calcite, 832–833
of calcite crystal, photo, 838
BJT. *See* Bipolar junction transistor
Blackbody radiation, 201–205
Planck's formula, 203
Rayleigh–Jeans law, 203
Stefan's black body radiation law, 203
Stefan's constant, 203
Wien's law, 277
Black's equation, 177, 178
Bloch wall, 706, 708–714, 759
potential energy, 710
thickness, 710
Bloch wavefunctions, 450, 461, 462
Bohr magneton, 286, 688, 759
Bohr model, 3
Bohr radius, 233, 239
Bohr's correspondence principle, 217
Boltzmann constant, 28
Boltzmann energy distribution, 39
Boltzmann factor, 38
Boltzmann statistics, 312–313, 363,
479, 661
Bond, general, 9–25
energy, 11, 99
length, 10
polar, 22
primary, 9–18, 102^c
rectangle, 78
secondary 18^c22, 102
switching, 155
twisting, 79
Bonding and types of solids, 9–25
Bonding (binding) energy, 11, 99
Bonding orbital, 286, 288
Bohr particle, 740
Bound charges, 559
Boundary conditions
dielectric, 614–620, 670
electric field, 794
magnetic field, 794
quantum mechanics, 210
Bragg diffraction condition, 194, 269, 356,
848–852
Bragg angle, 849
diffracted beam, 848
diffraction angle, 849
for cubic crystals, 851
Bragg distributed reflector, 568
Bragg's law. *See* Bragg diffraction
condition
Brass, 178, 182
Braze lattices, 95–98
unit cell geometry, 56, 97
Bronze, 178
Brewster's angle, 796, 841

- Bloch wave, 355, 357-361
 Buckminsterfullerene. See Carbon
 Built-in field, 570
 Built-in potential, 421-422, 478-480
 Built-in voltage, 570
 Bulk modulus, 99
- Capacitance
 definition, 584
 per unit volume, 634
 temperature coefficient (TCC), 636
 volume efficiency, 634
- Capacitor
 constructions, 631-634
 dielectric materials, 631
 dielectrics table, 635, 678
 electrolytic, 633
 equivalent circuits for parallel and series, 676
 polyester (PET), 636, 677
 polymeric film, 632
 tantalum, 634
 temperature coefficient, 636
 types compared, 631, 635, 678
- Carbon, 61-63
 amorphous, 63
 Buckminsterfullerene, 61-62
 diamond, 61, 62
 graphite, 61, 62
 lonsdaleite, 62
 properties (table), 63
- Carbon nanotube (CNT), 63, 336, 370
 field enhancement factor, 370
- Carrier concentration
 majority carrier, 410
 minority carrier, 410
 of extrinsic semiconductor, 388-392
 of intrinsic semiconductor, 380-387
 saturation temperature, 397
 temperature dependence of, 396-401
 extrinsic range, 398
 intrinsic range, 398
 ionization range, 397
- Cathode, 363
- Cathodoluminescence, 335, 820, 843
- Cauer, 6, 15, 99
- Cauchy coefficients (table), 782
- Cauchy dispersion equation, 783, 784
- CB. See Conduction band
- Ceramic, magnets, 726
- Ceramic materials, 22
- Chemisorption, 74
- Chip (integrated circuit), 570
- Circular birefringence, 835-837, 841
 media, 836
 optical activity, 835
 specific rotary power, 836, 844
- Cladding, 791
- Clauss-Mossotti equation, 593-594, 602, 670
- Coaxial cable failure, 628-631
 thermal breakdown, 678-679
- Cohesive field (coercivity), 715, 759
- Cohesive energy, 17
- Cole-Cole plots, 611-614
- Collimated beam, 36
- Common Base (CB) BJT configuration. See Bipolar junction transistor
- Compensated semiconductor, 461
- Compensation doping, 392-396, 461, 465
- Complementary principle, 269
- Complex dielectric constant, 605-611, 804-811
 loss angle, 610
 loss tangent, 607
 relaxation peak, 607
- Complex propagation constant, 805, 842
- Complex refractive index, 804-811, 842, 845-847
 extinction coefficient, 805, 842
 for a-Si, 806
 of InP, 808
 resonance absorption, 809-811
- Complex relative permittivity. See Complex dielectric constant
- Compton effect, 269
- Compton scattering, 199-202
- Conduction, 114-122, 316-422
 in metals, 318-320
 in semiconductors, 378-380
 in silver, 319
- Conduction band (CB), 302, 374-378, 461
- Conduction electron concentration, 115, 148
- Conduction electrons, 115, 155, 181, 299
- Conduction in solids
 electrical, 113-148
 thermal, 149-154
 in thin films, 166-167
- Conductivity
 activation energy for, 161
 electrical, 178, 180-181
 of extrinsic semiconductor, 389
 of Fermi level electrons in metal, 318
 of intrinsic semiconductor, 389
 of ionic crystals and glasses, 159-162
 lattice-scattering-limited, 124
 of metals, 114, 350-352, 367
 of nonmetals, 154-162
 of semiconductors, 155-159
 temperature dependence of, 122-125, 404-406
- Conductivity-mixture rule, 140
- Contact potential, 320-322
- Continuity equation, 422-427
 steady state, 424-427
 time-dependent, 422-423
- Continuous random network (CRN) model, 79
- Cooper pairs, 740, 759
- Coordination number (CN), 12, 17
 definition, 99
- Cose, 791
- Corona discharge, 622, 670
- Covalent bond, 99
- Covalent solids, 595-596
- Covariantly bonded solids, 11-13
- Critical angle, 842
- Critical electric field, 571
- Crystal, 99
- Crystal directions and planes, 56-61, 110
- Crystal lattice, 49-63
 different types, 97
- Crystal periodicity, 49
- strained around a point defect, 66
- Crystal structure, 50
- body-centered cubic (BCC), 51, 97, 109
 body-centered tetragonal (BCT), 97, 98
 close-packed, 13, 51
- CsCl, 54
- diamond cubic, 52, 109
- face-centered cubic (FCC), 14, 50, 55, 97, 100
 diffraction pattern (figure), 852
 hexagonal close-packed (HCP), 51
- NaCl, 51-53
- polymorphic, 61
- properties (table), 54
- study using x-ray diffraction, 849-852
 Laue technique, 850
 powder technique, 851
 types, 49-56, 97
- zinc blende (ZnS), 53, 109
- Crystal surface, 73-76
 absorption, 74
 adsorption, 74
 chemisorption, 74
 dangling bonds, 74, 81
 Kossel model, 74
 passivating layer, 74
 physisorption (physical adsorption), 74
 reconstructed, 74
 terrace-edge-kink model, 74
- Crystal symmetry, 98
- Crystal systems, 98
- Crystal types, 49-56
- Crystalline defects, 64-76
- Crystalline solid, 49
- Crystalline state, 49-63
- Crystallization, 99
 from melt, 70
 nuclei, 70
- Cubic crystals, 97
 interplanar separation, 851
- Cubic symmetry, 50
- Curie temperature, 648, 650, 670, 703-704
 table, 704
- Curie-Weiss law, 697
- Current in plane (CIP), 747
- Czochralski growth, 76-77
- Dangling bonds, 81
- De Broglie relationship, 205-207, 269
- Debye equations, 611-614, 670
 non-Debye relaxation, 614
- Debye loss peak, 612
- Debye heat capacity, 342-348
- Debye frequency, 344, 363
- Debye temperature, 344, 363
 table, 346
- Defect structures, 75-76
- Deformation, plastic (permanent), 69
- Degeneracy, 230
 three-fold, 230
- Degenerate semiconductor, 405, 461
- Degree of freedom, 28
- Delocalized electrons, 13
 electron cloud or gas, 13, 295
- Demagnetization, 717-719
- Density of states, 305-311, 315-316, 363, 380-382, 429
 effective density at CB edge, 382, 461
 effective density at VB edge, 362
- Density of vibrational states, 364
- Depinning. See Demagnetization
- Depletion capacitance, 498-499, 564
- Depletion region. See pn junction
- Depolarizing field, 657-658
 depolarizing factor, 657
- Diamagnetism, 696-698
- depinning, 748
- Dichroism, 833
- Dielectric breakdown, 620-631
 aging effects, 621
 breakdown mechanisms compared, 628
 in coaxial cables, 628-631, 678-679
 electrical tree, 626
 electrorefraction, 624-625, 671
 electromechanical, 624-625, 671
 electron avalanche breakdown, 623
 electronic, 623-624, 671
 external discharges, 677-678, 671
 in gases, 621-622
 internal discharges, 625-626, 671
 intrinsic, 623-624, 671
 in liquids, 622-623
- Lens, 603-611
- partial discharge, 621-622, 672
 in solid, 623-631
- surface tracking, 628, 671, 672
 table, 621

- Dielectric breakdown—*Cont.*
 thermal, 624, 673
 water trapping, 627
- Dielectric materials, 583–683
 constant. *See* Relative permittivity
 definition, 670
 dispersion relation, 666
 loss, 603–611, 670
 loss table, 611
 low k , 175
 properties (table), 678
 strength, 584, 620–621, 670. *See also*
 Dielectric breakdown
 strength table, 621
 volume efficiency, 634
- Dielectric mirrors, 803, 842
- Dielectric mixtures, 667–669
 effective dielectric constant, 667
- Lichtenegger formula, 668
 logarithmic mixture rules, 668
 Maxwell-Garnett formula, 669
- Dielectric resonance, 607, 662–667, 670
 frictional force, 663
- Lorentz dipole oscillator model, 664
 natural angular frequency, 664
 peak, 665
 relaxation peak, 665
 resonant angular frequency, 664
 restoring force, 663
 spring constant, 663
- Diffraction, 269, 848–852. *See also* Bragg diffraction condition
 angle, 849
 beam, 848
 patterns (figure), 193, 852
 study of crystal structure, 352–361,
 849–852
- Diffractrometer, 851
- Diffusion, 46–49, 99, 416–422, 461, 571
 coefficient, 48, 99, 420
 current, 484
 current density, 416, 418
 diffusion length, 424, 427, 483
 mean free path, 416–417
- Diffusion capacitance, 500–502, 571
- Diode action, 501
 dynamic conductance, 501
 dynamic (incremental) resistance,
 500, 571
- Diffusion coefficient, 420
- Diode. *See* $p-n$ Junction
 action, 501
 equation, 488
 laser, 266–269
 long, 572
 photodiodes, 564–566
 short, 486, 572
- Dipolar (orientational) polarization,
 598–600, 660–662, 670
- Langevin function, 661–662
 relaxation equation, 670
 relaxation process, 604, 670
 relaxation time, 604
- Dipole moment. *See* Electric dipole moment; Magnetic dipole moment
- Di pole relaxation, 604–607, 670
- Dipole-dipole interaction, 20–21
- Dirac, Paul Adrien Maurice, 314
- Direct recombination capture
 coefficient, 469
- Dislocations, 68–70, 99
 edge, 68, 99
 screw, 69, 102
- Dispersion relation, 364, 666, 842. *See also* Refractive index
- Dispersive medium, 785, 842
- Domains. *See* Ferromagnetism
- Donors, 389, 461
- Doping, 388–396
 compensation, 392–394
n-type, 384, 388–390
p-type, 384, 390–392
- Doppler effect, 265, 269
- Double heterostructure (DH) device, 547
- Drift mobility, 117, 401–404
 definition, 178
 due to ionic conduction, 162
 effective, 127, 403
 impurity dependence, 401–404
 impurity-scattering-limited, 127, 403, 462
 lattice-scattering-limited, 127, 402, 463
 tables, 146, 386
 temperature dependence, 401–404
- Drift velocity, 114, 118, 121, 157,
 178, 379
- Drude model, 114–122, 319
- Dulong-Petit rule, 30, 344
- Dynamic (incremental) resistance,
 500–502, 571
- Early effect, 512, 570
- Early voltage, 538
- Eddy currents and losses, 760, 766
- Effective mass, 303–305, 364, 379,
 451–455, 462
- EHP. *See* Electron-hole pairs
- Eigenenergy, 214
- Eigencalculation, 210
- Einstein relation, 188, 419, 462
- E-k diagrams, 448–452
- Elastic modules, 24–25, 100
- Electric dipole moment, 19, 100, 583,
 585–589, 670
 definition, 19, 100, 670
 induced, 20, 586, 779–780
 in nonuniform electric field, 674–675
 permanent, 15, 19, 598
 relaxation time, 604
- Electric displacement, 654–658
 depolarizing factor, 657
 depolarizing field, 657
- Electric susceptibility, 591, 671
- Electrical conductivity, 178, 180–181
- Electrical contacts, 143–144
- Electrical noise, 42–45, 108. *See also* Noise
 Johnson resistor noise equation, 44
 rms noise voltage, 44
- Electrochemical potential, 321
- Electrodeposition, 167
- Electroluminescence, 544, 820, 843
 injection, 823
- Electromechanical coupling factor, 642
- Electromigration, 172
 accelerated failure tests, 177
 of Al-Cu interconnects, 189
 barrier, 177
 definition, 178
 hillock, 177
 mean time to 50 percent failure, 177
 rate, 177
 void, 177
- Electronization and Black's equation,
 176–177
- Electron
 average energy in C/B, 385, 462
 average energy in metal, 317, 363
 concentration in C/B, 382, 388–390, 392
 conduction electrons, 115, 155, 181, 299
 confined, 212–217
 crystal momentum 451, 454, 813–814
 current due to, 419
 diffraction in crystals, 352–361
 diffraction patterns, 206
 diffusion current density, 418
 effective mass, 303–305, 364, 379,
 453–455, 462
- effective speed in metals, 317
- energy in hydrogenic atom, 236–241
- energy in metals, 317
- Fermi-Dirac statistics, 123
- gas, 295
- group velocity, 454
- magnetic dipole moment, 248–252
- mean recombination time (t_m junction),
 487
- mobility, 379
- momentum, 214
- motion and drift, 452–453
- in a potential box, 228–230
- spin, 245–247, 271
- spin resonance (ESR), 280
- standing wave, 353
- surface scattering, 168–172
 as a wave, 205–212, 352–354
- wavefunction in hydrogenic atom,
 231–236
- wavefunction in infinite PE well, 229
- wavelength, 207
- Electron affinity, 6, 100, 375, 436, 462
- Electron beam deposition, 80, 167
- Electron drift mobility. *See* Drift mobility
- Electron spin resonance (ESR), 280
- Electronegativity, 22, 100
- Electron-hole pairs, 376–378
 generation, 302, 376–378, 383, 410–414
 mean thermal generation time, 490
 recombination, 377–378, 412, 457–458
- Electronic impurity, 546
- Electronic (quantum) state, 234, 247
- Electro-optic effects, 837–841, 842
 field induced refractive index, 838
 Kerr effect, 838, 842
 noncentrosymmetric crystals, 838
- Pockels effect, 838, 843
- Electroresistivity, 431, 463
- Energy bands, 291–295, 305–308
- Energy density, 269, 695
- Energy gap (E_g). *See* Bandgap
- Energy, quantized, 214, 236–241
 ground state energy, 215
 in the crystal, 462
 infinite potential well, 230
- Energy versus crystal momentum plot. *See*
 E-k diagrams
- Epitaxial layer, 544, 571
- Equilibrium, 100
- Equilibrium state, 41, 100
- Eutectic composition, 93, 100
- Eutectic phase diagram, 90–95
- Eutectic point, 91
- Eutectic transformation, 92
- Evanescent wave, 798
 attenuation coefficient, 798
 penetration depth, 799
- Excess carrier concentration, 410, 462,
 468–469
- Exchange integral, 702
- Exchange interaction, 700–703, 760
- Excitation
 activator, 822
 host, 822
- Excited atom, 6
- Extended states, 458, 462
- External quantum efficiency, 571
- External reflection, 798, 801–802, 846
- Extinction coefficient, 805, 842
- Extrinsic semiconductors, 388–396, 462,
 464–465
- Family of directions in a crystal, 58
- Family of planes in a crystal, 59
- Fermi energy, 294, 314, 317, 320–322,
 364, 366, 435–436, 462
- in intrinsic semiconductor, 384

- in a metal, 315–317
table, 295
- Fermi surface, 359
- Fermi–Dirac statistics, 123, 312–315, 364
- Ferrimagnetism, 700, 760
- Ferrite antenna, 767–768
- Ferrites, 723, 760, 767–768. See also Ferrimagnetism
- Ferroelectric crystals, 647–653, 671
ferroelectric axis, 649
- Ferromagnetism, 699, 760
closure domains, 706
domain wall energy, 709–711, 760, 764–765
domain wall motion, 712–713
domain walls, 706, 708–711, 760
domains, 699, 705–706, 761
electrostatic interaction energy, 701
energy band model, 742–744
magnetocrystalline anisotropy, 706–708
materials table, 704
ordering, 699
origin, 700–703
polycrystalline materials, 713–717
- Fick's first law, 418
- Field assisted tunneling probability, 334
- Field effect transistor, 571. See JFET; MOSFET
- Field emission, 332–337, 364
- Field emission tip, 335
anode, 335
gate, 335
Spindt tip cathode, 335
- Field enhancement factor, 370
- Fluence
energy, 275
photons, 276
- Fluorescence, 820, 842
- Flux, defined, 269
luminous, 853
of particles, 416
of photons, 198, 853
photometric, 853
radiant, 853
- Flux quantization, 758–759
- Forward bias, 478–489. See also pn junction
- Fourier's law, 150, 178
- Fowler–Nordheim
anode current, 335
equation, 334
field emission current, 370
- Franck–Hertz, 244–245
- Free space charge density, 592
- Frankel defect, 66, 100
- Fresnel's equations, 793–803, 842
- Frenkel's optical indicatrix, defined, 829–832, 843
extraordinary wave, 829
ordinary wave, 829
- Frequency, resonant
antiresonant, 645
mechanical resonant, 645
natural angular frequency, 664
resonant angular frequency, 664
- Fuchs–Sondheimer equation, 170
- GaAs, 52, 386, 466
- Gas constant, 25
- Gas pressure (kinetic theory), 27
- Gauge factor, 434
- Gauss's law, 614–620, 654–658, 671
- Giant magnetoresistance (GMR), 744–748, 751, 760. See also Magnetoresistance
table, 747
- Glasses, 78–82. See also Amorphous solids
melt spinning, 79
- GMR. See Giant magnetoresistance
- Grain, 70, 100
Grain boundaries, 70–73, 100
disordered, 72
- Grain coarsening (growth), 73
- Ground state, 215, 269
energy, 215, 237
- Group index, 784–787, 842
definition, 785
- Group velocity, 764, 784–787, 842
in medium, 785
in vacuum, 785
- Gruneisen's model of thermal expansion, 361–363
Gruneisen's law, 362, 371
Gruneisen's parameter (table), 363
- Gyromagnetic ratio, 687
- Hall coefficient, 146, 178, 359
for ambipolar conduction, 158
for intrinsic Si, 158–159
- Hall devices, 145–148
- Hall effect, 145–148, 178, 185–186
in semiconductors, 156–159, 468
- Hall field, 146
- Hall mobility, 148
- Hard disk storage, 750–752
magnetic bit tracks, 751
magnetoresistance sensor, 751
thin film heads, 752
- Hard magnetic materials, 724–729, 761
design, 768–769
neodymium–iron–boron, 727
rare earth cobalt, 726–727
single domain particles, 724, 761
table, 724
- Harmonic oscillator, 337–342, 364
average energy, 343
energy, 338
potential energy of, 338
- Schrödinger equation, 338
zero point energy, 339, 365
- Heat, 41, 100
- Heat capacity, 28, 100
- Heat current, 153
- Heat of fusion, 84
- Heat, thermal fluctuation and noise, 40–45
noise in an RLC circuit, 44
rms noise voltage, 44
thermal equilibrium, 40
- Heisenberg's uncertainty principle, 217–220, 269, 277
for energy and time, 219
for position and momentum, 218
- Helium atom, 254–256
- Helium–neon laser, 261–264
efficiency, 264
- Hervé–Vandamme relationship, 845
- Heterogeneous media, 667–669
Lichtenecker formula, 668
logarithmic mixture rules, 668
Maxwell–Garnett formula, 669
- Heterogeneous mixture (multiphase solid), 139–143, 178
- Heterojunction, 547, 571
- Heterostructure devices, 544, 547
confining layers, 548
double heterostructure, 547
- Hexagonal crystals, 52, 97
- HF resistance of conductor, 163–166
- Hole, 155, 302, 373, 376–378, 455–456
concentration in VB, 382, 391–392
current due to, 419
- diffusion current density, 418
- diffusion length, 483
- effective mass, 380, 456
- mean recombination time ($\tau_{\text{re}}^{\text{junction}}$), 487
- mobility, 380
- Homogeneous mixture, 178–179
- Homojunction, 547, 571
- Host excitation, 822
- Host matrix, 820, 843
- Human eye, 273–275
photopic vision, 273
scotopic vision, 273
- Hund's rule, 256–258, 268, 281
- Hybrid orbital, 300
- Hybridization, 300
- Hydrogen bond, 19
- Hydrogenated amorphous silicon. See a-Si:H
- Hydrogenic atom, 231–233
electron wavefunctions, 231–236
line spectra, 278
- Hysteresis loop, 715–719, 761
energy dissipated per unit volume, 718–719
loss, 761, 766
- Image charges theorem, 332
- Impact ionization, 503, 571
- Impurities, 64–66
- Incandescence, 820
- Inductance, 163, 693–694
of a solenoid, 763
toroid, 694, 723, 765
- Infinite potential well, 212–217
- Insulation strength. See also Dielectric breakdown
aging, 627, 671
- Integrated circuit (IC), 571
- Intensity, defined, 269
of EM waves, 192
of light, 192, 197–198, 799
- Interconnects, 172–176, 179, 188
aspect ratio, 175
effective multilevel capacitance, 174
low-k dielectric materials, 175
multilevel interconnect delay time, 175
RC time constant, 173, 175–176
- Interfacial polarization. See Polarization
- Internal discharges. See Dielectric breakdown
- Internal reflection, 796–797, 800–801, 846
- Interplanar separation in cubic crystals, 851
- Interstitial site, 45, 101
impurity, 66, 83–84
- Intrinsic angular momentum. See Angular momentum; Spin
- Intrinsic concentration (n_i), 383, 462, 485
- Intrinsic semiconductors, 374–387, 462
- Inversion, 532–535, 571. See also MOSFET
- Ion implantation, 541–543, 571
- Ionic conduction, 179
- Ionic crystals, 17
- Ionically bonded solids, 14–18, 104
table, 21
- Ionization energy, 6, 15, 101, 237, 462
for nth shell, 237
of He^+ , 240
- Irradiance, 787–789
average, 788, 842
instantaneous, 788, 842
- Isoelectronic impurity, 546, 572
- Isomorphous, 101
- Isomorphous alloys, 83–88
- Isomorphous phase diagram, 84, 179
- Isotropic substance, 101

- JFET, 522–532, 571
 amplifier, 528–532, 577
 channel, 523, 570
 characteristics, 524, 528
 common source amplifier, 529
 constant current region, 528
 current saturation region, 528
 drain, 522
 drain current, 523
 field effect, 528
 gate, 522
 general principles, 522–528
 nonlinearity, 532
 pentode region, 528
 pinch-off condition, 525–526
 pinch-off voltage, 524, 572, 576–577
 quiescent point, 529
 source, 522
 transconductance, 531
 voltage gain, small-signal, 531
 Johnson resistor noise equation, 44
 Josephson effect, 756–758
 dc characteristics, 757
 definition of 1 V, 758
 Joule's law, 179
 Junction field effect transistor. *See* JFET
- K.** *See* Wavevector
 Kamerling Onnes, Heike, 730
 Kerr effect, 838, 842
 coefficients, table, 840
 Kirby, Jack, 474
 Kinetic (molecular) theory, 25–36, 101
 degree of freedom, 28
 equipartition of energy theorem, 28
 heat capacity, 28. *See also* Dulong-Petit rule
 mean kinetic energy, 27–28
 mean speed, 27, 30–31, 115
 thermal fluctuations, 40–45
 Kondo model, 74
 Kramers-Kronig relation, 806, 842–843
- Lamellae, 93
 Langevin function, 661–662
 Lasers, 258–267, 269–270
 cavity modes, 265
 diode, 266–269
 Doppler effect, 265
 He-Ne laser. *See* Helium-neon laser
 lasting emission, 261
 linewidth, 265
 long-lived states, 260
 metastable state, 260
 output spectrum, 265–267
 population inversion, 259
 pump energy level, 260
 pumping, 260, 270
 semiconductor, 475, 566–569
 single-frequency, 569
 single-mode, 569
 stimulated emission, 259, 271
 threshold current, 569
- Lattice, 50, 95, 101. *See also* Bravais lattices
 cut-off frequency, 340
 energy, 18
 parameter, 50, 56, 96, 101
 space, 95
 waves, 337–342, 347, 364
- Lattice vibrations, 339–350
 density of states, 343, 363
 heat capacity, 344
 internal energy, 343
 modes, 341–342, 364
 state, 341, 364
- Lattice-scattering-limited conductivity, 174
- Lase technique, 850
 Law of the junction, 482–483, 572
 Lenard-Jones 6–12 potential energy curve, 23
- Lever rule, 144
- Lichtenecker formula, 668
- Light absorption, 804–811
 and conductivity, 808
- Light as wave, 191–194
- Light emitting diodes (LEDs), 475, 543–551
 characteristics, 548–551
 electroluminescence, 544
 external efficiency, 546
 heterojunction high intensity, 547–548
 linewidth, 549, 572, 579
 materials, 546
 principles, 543–546
 spectral linewidths, 550–551, 579
 substrate, 544
 turn-on (cut-in) voltage, 550, 573
- Light propagation, 804–805
 attenuated, 805
 conduction loss, 805
 losses, 804
- Light scattering, 804, 816–817, 844
- Light waves, 774–776
- Line defects, 68–70
 strain field, 68
- Linear combination of atomic orbitals (LCAO), 287, 364
- Liquids curve, 85
- Local field, 593–594, 658–660, 671–672
- Localized states, 459, 463
- Long range order, 49, 78
- Longitidule, 62
- Lorentz dipole oscillator model, 664
- Lorentz equation, 658–660
- Lorentz field, 593–594
- Lorentz force, 145, 179
- Lorentz number, 150. *See also* Wiedemann-Franz-Lorenz's law
- Loss angle, 610
- Loss tangent (factor), 607, 672
- Lumens, 853
- Luminescence, 820–825
 activator, 820, 841
 activator excitation, 822
 cathodoluminescence, 820, 843
 electroluminescence, 544, 820, 843
 fluorescence, 820, 842
 host excitation, 822
 host matrix, 820, 843
 phosphorescence, 821, 843
 photoluminescence, 820, 843
 radiative recombination center, 822
 Stoke's shift, 822, 844
- X-ray, 820
- Luminescent (luminescence centers). *See* Activator
- Luminous efficacy, 854
- Luminous (photometric) flux or power, 270, 273, 853
 lumens, 853
- Lymne series, 278
- Madelung constant, 17
- Magnet, permanent, 268
 table, 768
 with yoke and air gap, 768–769
- Magnetic bit tracks, 751
- Magnetic dipole moment, 685–686, 761
 atomic, 687–688
 definition, 686
 of electron, 248–252
 orbital, 249, 687
 per unit volume, 689
 potential energy, 249–250
 spin, 249, 687
- Magnetic domains. *See* Ferromagnetism
- Magnetic field (B), 179, 761, 787–789
 in a gap, 771
 intensity, 691–692
 transverse, 793
- Magnetic field intensity (strength). *See* Magnetizing field (H)
- Magnetic flux, 693, 761
 quantization, 758–759
- Magnetic field density. *See* Magnetic field
- Magnetic induction. *See* Magnetic field
- Magnetic materials classification, 696–700
 amorphous, 722
 soft and hard materials, 719–721
 table, 697
- Magnetic moment. *See* Magnetic dipole moment
- Magnetic permeability, 179, 692–696,
 761. *See also* Relative permeability
 quantities table, 693
 relative, 692, 762
- Magnetic pressure, 769–770
- Magnetic quantities and units, 693
- Magnetic quantum number, 232, 270
- Magnetic recording, 749–756
 fringe magnetic field, 749, 771
 general principles, 749–750, 770–771
 hard disk storage, 750–752
 head materials, 752–753
 inductive recording heads, 749
 longitudinal recording, 749
 magnetic bit tracks, 751
 materials tables, 754, 755
 storage media, 753–756, 770–771
 thin film heads, 752
- Magnetic susceptibility, 692–696, 762
- Magnesium and energy band diagrams, 740–744
- Energy band model of ferromagnetism, 742–744
- Pauli-Spin paramagnetism, 740–742
- Magnetization current, 690, 762
- Magnetization of matter, 683–696
- Magnetization vector (M), 688–690, 762
 and surface currents, 690, 762
- Magnetization versus H, 713–717
 coercivity, 715, 759
 initial magnetization, 716
 remanent (residual), 715, 762–763
 saturation, 703–704, 717, 763
- Magnetizing field (B), 691–692, 761
 conduction current, 691
- Magnetocrystalline anisotropy, 706–708,
 762
 easy direction, 706, 708, 760
 energy, 708, 762
 hard direction, 708, 761
- Magnetometer, 179
- Magnetoresistance, anisotropic and giant,
 744–748, 762
 current in plane (CIP), 747
 ferromagnetic layer, 745
 spacer, 745
 spin valve, 747
- Magnetostatic energy, 705, 762
 density, 696
 per unit volume, 694–696
- Magnetotriction, 711–712, 762
 saturation strain, 711
- Magnetostatic energy, 711, 762
 constant, 711
- Majority carrier, 410, 463
 Mass action law (semiconductors),
 383, 463
 with bandgap narrowing, 576
- Mass fractions, 8–9, 88

- Matthiessen's rule, 125–134, 179, 181
 combined with Nordheim's rule, 137,
 142–143
 Maxwell's equations, 776
 Maxwell-Boltzmann distribution function,
 37–39
 Maxwell's principle of equipartition of
 energy, 28, 42–43
 Mayadas-Shatzkes formula, 168
 Mean free path
 of electron, 122, 123, 179
 in polycrystalline sample, 168
 in thin film, 169
 of gas molecules, 106–107
 Mean free time, 117, 119, 121, 179
 Mean frequency of collisions, 118
 Mean kinetic energy and temperature,
 25–31
 Mean scattering time. See Mean free
 time
 Mean speed of molecules, 39–40
 Mean square free time, 121
 Mean thermal expansion coefficient, 35
 Mechanical work, 101
 Meissner effect, 731, 762
 Melt spinning, 79
 Metallic bonding, 13, 101
 Metallurgical junction (semiconductors),
 476, 572
 Metal-metal contacts, 320–322
 Metal-oxide semiconductors (MOS),
 532–533, 572. See also MOSFET
 threshold voltage, 539–541, 573
 Metal-oxide semiconductors in field effect
 transistor. See MOSFET
 Metals, band theory, 352–361
 free electron model of, 315–317
 quantum theory of, 315–320
 Miller indices, 58–61, 101
 Minority carrier, 410–416, 463
 diffusion, 483
 diffusion length, 463
 excess concentration of, 410–416
 injection, 407–416, 475, 481–483,
 572
 lifetime, 412, 463
 profiles (hyperbolic), 574
 recombination time, 412, 573
 Miscibility, 101
 Mixed bonding, 22–25
 Mixture rules, 139–144, 184
 Mobility. See Drift mobility
 Mode number, 265
 Modern theory of solids, 285–371
 Molar fractions, 8
 Molar heat capacity, 28, 101, 343
 Mole, 8, 101
 Molecular orbital, 286
 Molecular orbital theory of bonding,
 285–290
 hydrogen molecule, 285–289
 Molecular orbital wavefunction, 364
 Molecular solids, 21
 Molecular speeds, distribution (Stern-type
 experiment), 36
 Molecular velocity and energy
 distribution, 36–40
 Monoclinic crystals, 97
 Moseley relation, 279
 MOSFET, 532–543, 572
 accumulation, 570
 amplifier, 577–578
 depletion layer, 532–534, 571
 early voltage, 538
 enhancement, 535–539, 571
 field effect and inversion, 532–535
 inversion layer, 534
 ion implanted, 541–543
 MOST, 572
- NMOS, 572
 PMOS, 572
 silicon gate technology, 542
 threshold voltage, 539–541, 573
 Moss's rule, 845
 Motion of a diatomic molecule, 28–29
 rotational, 28–29
 translational, 28–29
 Mott-Jones equations, 324
 Müller, K. Alex, 684
 Multilevel interconnect
 delay time, 175
 effective capacitance, 174
 RC time constant, 175
- Nanotube, carbon, 63, 336, 370
 Natural (resonance) frequency of an atom,
 780, 846
 Nearly free electron model, 449
 Néel temperature, 699
 Newton's second law, 25
 Nichrome, 135
 NMOS. See MOSFET
 Nondegenerate semiconductor, 406–407,
 463
 Node, 215
 Noise, 40–45. See also Electrical
 noise
 Nonstoichiometry, 75–76
 Nordheim's coefficient, 136
 table, 136
 Nordheim's rule, 134–139, 179, 182
 combined with Matthiessen's rule, 137,
 142–143
 Normalization condition in quantum
 mechanics, 214
 n-type doping, 388–390
 energy-band diagram, 389
 Nucleate (solidify), 84
- Ohm's law of electrical conduction,
 118, 150
 Ohmic contact, 443–448, 463
 Optic axis, 829–830, 843
 principal, 827–828, 843
 Optical absorption, 427–431, 804–811,
 841
 absorption coefficient, 428, 813
 band-to-band (interband), 429,
 813–816
 and conductivity, 808
 free carrier, 805, 847
 lattice, 811–812
 penetration depth, 429, 813
 Reusserian absorption, 811
 upper cut-off wavelength, 813
 Optical activity, 835, 843
 specific rotary power, 836
 Optical amplifiers, 267
 Optical anisotropy, 827–833, 841
 Optical fiber, 791, 817–819
 attenuation in, 817–819
 cladding, 791
 in communications, 791–792
 core, 791
 Optical fiber amplifiers, 267–268
 Erbium (Er^{3+} ion) doped, 267, 282
 long-lived energy level, 267
 Optical field, 774
 Optical indicatrix. See Fresnel's optical
 indicatrix
 Optical power. See Radiant power
 Optical properties of materials, 773–847
 Optical pumping, 260, 270
 Optically isotropic media, 778
 crystals, 827
 Orbital, 234, 270, 364
 magnetic moment, 249
 Orbital wavefunction, 270, 364
- Orientational polarization. See Dipolar
 polarization
 Orthorhombic crystal, 97
- Parallel rule of mixtures, 140
 Paramagnetism, 698, 762
 Pauli spin, 740–742, 764
 Parity, 216
 even, 216
 odd, 216
 Partial discharge, 618, 621–622, 672
 Particle flux, 416–420
 Particle statistics. See Statistics
 Paschen
 curves, 677
 series, 278
 Passivated Emitter Rear Locally diffused
 cells (PERL), 561–562
 Passive device, defined, 572
 Pauli exclusion principle, 115, 254–256,
 270, 312–313, 701
 Pauli spin magnetization, 698, 740–742, 764
 Pauling scale of electronegativity, 22
 PECVD. See Plasma-enhanced chemical
 vapor deposition
 Peltier, coefficient, 447–448
 device, 444
 effect, 445, 463
 figure of merit (FOM), 471–472
 maximum cooling rate, 472
 Penetration depth, 429, 813
 Periodic array of points in space. See
 Crystal structure
 PERL. See Passivated Emitter Rear
 Locally diffused cells
 Permanent magnet, (BH_{max}) , 727–729
 Permeability, absolute, 692. See also
 Magnetic permeability, Relative
 permeability
 initial, 720–721, 761
 maximum, 720–721, 762
 relative, 692, 762
 Permittivity. See Relative permittivity
 Phase, 83, 101, 179
 coiled structure, 87
 diagrams, 84–88, 101
 equilibrium, 87
 eutectic, 90–95
 lever rule, 87
 liquidus curve, 85
 nonequilibrium cooling, 87
 solidus curve, 85
 tie line, 88
 Phonons, 337–352, 364, 409, 463, 815
 dispersion relation, 340, 364
 energy, 340
 group velocity, 341
 lattice cut-off frequency, 340
 momentum, 340, 815
 phosphors, 820–825, 843
 table, 824
 Phosphorescence, 821, 843
 Photoconductivity, 414–416, 463
 Photodiectors, 475
 Photodiodes, 564–566
 Photoelectric effect, 194–199, 270, 276
 Photogeneration, 376, 410–412, 463
 carrier kinetic energy, 473
 steady state rate, 469
 Photojunction, 463
 Photometric flux. See Luminous flux or
 power
 Photometry, 853
 Photon, 191–205, 270, 272
 efficiency, quantum, 276
 energy, 196, 200
 flux, 198, 853
 momentum, 199, 200
 picture, 198

- Photon amplification, 258–261
 Photovoltaic devices, principles, 551–559.
See also Solar cell
 Photoresponse time, 413–414
 Physical vapor deposition (PVD), 167
 Physisorption, 74
 Piezoelectric
 antiresonant frequency, 645
 bender, 680
 coefficients, 641, 681
 detectors, 681
 electromechanical coupling factor, 642
 inductance, 646
 materials, 672
 mechanical resonant frequency, 645
 poling, 643, 672
 properties table, 642
 quartz oscillator and filters, 644–647
 spark generator, 643–644
 transducer, 641, 673
 voltage coefficient, 644, 680
 Piezoelectricity, 638–647
 center of symmetry, 639
 nanosymmetric, 640
 Piezoresistive strain gauge, 434–435
 Piezoresistivity, 431–435, 463, 470
 Cantilever equations, 470
 diaphragm, 434
 piezoresistive coefficient, 433, 463
 pin Diodes, 564–566
 depletion layer capacitance, 564
 Pinch-off, 524–528, 537, 572, 576–577
 Planar concentration of atoms, 60, 101,
 109–110
 Planar defects, 70–73
 Planck, Max, 203
 constant, 196
 Plane of incidence, 793
 Plasma-enhanced chemical vapor
 deposition (PECVD), 82
 PLZT, 672
 PMOS. *See MOSFET*
 pn Junction, 476–493
 band diagram, 494–498
 built-in potential, 478–480
 depletion capacitance, 494–499, 571
 depletion region, 477, 571
 depletion region width, 479, 498
 diffusion capacitance, 500–502
 diffusion current, 481–487
 forward bias, 481–487, 571
 heterojunction, 547
 homojunction, 547
 ideal diode equation, 485
 ideality factor, 488
 incremental resistance, 500–502
 I–V characteristics, 497
 I–V for Ge, Si and GaAs, 486, 489
 no bias, 476–481
 recombination current, 488, 572
 reverse bias, 489–493
 reverse saturation current, 485, 490,
 572
 short diode, 486
 space charge layer (SCL), 477, 571
 storage capacitance. *See Diffusion
 capacitance*
 temperature dependence, 574
 total current, 487–489
 total reverse current, 491
 pn Junction band diagrams 494–498
 built-in voltage from band diagrams,
 498
 forward and reverse bias, 495–498
 open circuit, 494–495
 Pockels cell plane modulator, 840, 847
 Pockels effect, 838, 843
 coefficients, table, 840
 Point defects, 64–68
 Frenkel, 66
 impurities, 64–68
 interstitial, 66
 Schottky, 66
 substitutional, 65
 thermodynamic, 64
 Poisson ratio, 186
 Polar molecules, 19
 Polarizability, 586, 588, 781. *See
 Polarization*
 defined, 586, 672
 dipolar (orientational), 662
 ionic, 664
 orientational, 662
 table, 588
 Polarization, 101, 583–603
 charges, 591
 definition, 585–586, 672
 dipolar, 588–600, 660–662, 670
 electronic, 585–589, 595–596, 671,
 781
 electrostatic bond, 671
 induced, 586, 664, 671
 interfacial, 600–601, 671
 ionic, 597–598, 602, 662–667, 671,
 811
 mechanisms, 597–603
 orientational. *See Polarization, dipolar*
 relaxation peak, 665
 table, 602
 total, 601–603
 vector, 589–593, 672
 Polarization angle. *See Brewster's angle*
 Polarization modulator, 841
 halfwave voltage, 841
 Polarization of EM wave, 796, 825–827,
 843
 circular, 826, 841
 elliptical, 827
 linear, 796, 825
 plane, 825
 Polarized molecule, 20
 Poling, 643, 672
 Polycrystalline films and grain boundary
 scattering, 167–168
 Polymorphism, 61, 102
 Polyisilicon gate (poly-Si), 541–543, 572
 Population inversion, 259, 270. *See also
 Lasers*
 Powder technique, 851
 Poynting vector, 787–789, 843
 Primary α , 94
 Primary bonds, 18
 Principal optic axis, 827–828
 Principal refractive index, 827
 Probability. *See Statistics*
 Probability of electron scattering, 119
 Probability per unit energy, 39
 Preexisting (primary) α , 94
 Properties of electrons in a band,
 296–299
 Property, definition, 102
 p-type doping, 390–392
 energy-band diagram, 391
 Pumping, 260, 270
 PV work, 101
 Pyroelectric, crystals, 647–653
 coefficients, 650
 current density, 652
 current responsivity, 652
 detector, 651–652, 681–682
 electric time constant, 682
 material, 672
 table, 650
 thermal time constant, 682
 voltage responsivity, 652
 PZT, 672, 681
 Q-factor, 672
 Quantization
 of angular momentum, 241–245
 of energy, 230, 236–241
 space, 241–245, 247
 Quantum leak. *See Tunneling*
 Quantum numbers, 214, 232
 magnetic, 232, 241, 270
 orbital angular momentum, 232,
 241–245, 270
 principal, 232, 270
 quantum state, 234
 spin magnetic, 246, 271
 Quantum physics, 191–283
 harmonic oscillator, 337–342
 tunneling, 221–228, 271, 278
 Quartz oscillator and filter, 644–647
 Quartz crystal
 equivalent circuit, 646
 inductance, 647
 Quiescent point, 529
 Radial function, 233–236
 Radial probability density, 233
 function, 236
 Radiant, 270
 flux, 269, 271, 853
 power, 271
 Radiant emittance, 203. *See also Black-
 body radiation*
 Radiation, 271
 brightness, 853–854
 Radiative recombination center, 822
 Radiometry, 853
 flux in, 269, 853
 Random motion, 416–422
 Rare earth cobalt, magnets, 726
 Rayleigh scattering, 816–817
 in silica, 819
 Rayleigh-Jeans law, 203
 Recombination, 383, 407–409, 457–458,
 463, 469
 capture coefficient, direct, 469
 current, 487–489, 572
 direct, 407–409, 469
 indirect, 407–409, 457–458
 lifetime, 469
 mean recombination time, 412, 487
 and minority carrier injection, 407–416
 rate, 469
 Reflectance, 799–803, 807, 843
 infrared, 811
 Reflection of light, 793–799
 coefficient, 793–799, 807, 843
 external, 797, 801–802, 846
 internal, 796, 797, 800–801, 846
 at normal incidence, 796
 phase changes, 795
 Refracted light, 789–790, 843
 phase changes, 795
 transmission coefficients, 793–799,
 844
 Refractive index, 777–779, 844
 complex, 804–811
 definition, 777
 dispersion relation, 773, 781–782,
 842, 846
 dispersion relation in diamond, 846
 dispersion relation in GaAs, 783
 field emission, 838
 isotropic, 777
 at low frequencies, 778
 temperature coefficient, 845
 versus wavelength, 779–784
 Relative atomic mass. *See Atomic mass*
 Relative permeability, 692, 762
 Relative permittivity, 583, 584–585, 672,
 673, 778, 781, 844

- complex, 605, 670, 804
definition, 584, 672
effective, 667
loss angle, 610
real and imaginary, 605–614
table, 602, 610
Relaxation peak, 607
Relaxation process, 606
Relaxation time, 117, 179, 604, 672
Remanence. *See under Magnetization*
Remanent magnetization. *See under Magnetization*
Residual resistivity, 128, 179
Resistivity, effective, 140
Resistivity index (n), 132
Resistivity of metals (Table), 129
due to impurities, 138
graph, 130
Resistivity of mixtures and porous materials, 139–144
Resistivity of thin films, 167–172
Resistivity-mixure rule, 140, 142
Resonant frequency. *See Frequency, resonant*
Restriction absorption, 811–812
Restriction band, 811
Retarding plates, 833–835, 844, 847
half-wave retarder, 834
quarter-wave retarder, 835
quartz retarder, 835
relative phase shift, 834
retardation, defined, 834
Reverse bias, 489–493, 572. *See also pn junction*
RF heating, 77
Rhombohedral crystal, 97
Richardson-Dushman equation, 328–332, 333
Root mean square velocity, 40
Rydberg constant, 245

Saturated solution, 102
Saturation of magnetism, 703–704
Schottky defect, 66, 102
Schottky effect, 332–337
Schottky coefficient, 331
Schottky junction, 435–443, 464
built-in electric field, 437
built-in potential, 437
depletion region, 437
diode, 435–440
energy band diagram, 436, 438, 440
I-V characteristic, 438
Schottky barrier height, 437
Schottky junction equation, 440
solar cell, 440–443
space charge layer (SCL), 437
Schrödinger's equation, 208–212, 271, 450
for three dimension, 209
time dependent, 208–209
time independent, 208–212, 271
SCL. *See Space charge layer*
Screw dislocation, 69, 102.
line, 69
Secondary bonding, 18–22, 102
Secondary emission, 368–369
Seebeck effect, 322–328, 364–365
in semiconductors, 472–473
Mott and Jones equation, 324
Seebeck coefficient, 322–323
Seed, 77
Selection rules, 242–243, 271
Selmeier coefficients, 782
Selmeier equation, 782, 845
Semiconductor bonding, 299–302
Semiconductor devices, 475–581
ultimate limits to device performance, 578
Semiconductor optical amplifiers, 566–569
active layer, 567
optical amplification, 568
Semiconductors, 299–303, 373–473
conduction band (CB), 302
degenerate and non-degenerate, 406–407
direct and indirect bandgap, 448–458, 814–815
strain gauge, 434–435
tables, 366, 386
valence band (VB), 301
Series rule of mixtures, 140
Shell model, 3
Shockley, William, 372, 473
Shockley equation, 485, 572
Short-range order, 79
Silicon, 80, 299–301, 374–380
amorphous, 80–82, 459. *See also a-Si:H*
conduction band, 302
crystalline, 80–82
energy band diagram, 374
hybrid crystals, 300
hydrogenated amorphous silicon
(a-Si:H), 82, 459
properties (table), 674
valence band, 301
zone refining, 88–90
Silicon gate technology. *See Polysilicon gate*
Silicon single crystal growth, 76–77
Skin depth for conduction, 163
Skin effect in inductor, 166
Skin effect: HF resistance of conductor, 163–166, 179
at 60 Hz, 188
Small signal equivalent circuit, 572
Sohl's law, 790–792, 844
Soft magnetic materials, 721–724, 763
table, 722
Solar cell, 475, 551–563, 581
anti-reflection coating, 551, 802–803, 841, 846
fill factor, 558, 571
finger electrodes, 551
I-V characteristics, 556–557
load line, 557
materials, devices and efficiencies, 561–563
maximum power delivered, 580
normalized current and voltage, 580
open circuit voltage, 552, 558–559
operating point, 557
passivated emitter rear locally diffused cells (PERL), 561–562
photocurrent, 553, 572
photovoltaic device principles, 551–559
power delivered to the load, 557
Schottky junction, 440–443
series resistance, 559–561, 581
short circuit current, 556
shunt (parallel) resistance, 559–561, 581
total current, 556
Soilder (Pb-Sn), 90–95, 111
Solid solution and Nordheim's rule, 134–139, 182
Cu-Au, 137
Cu-Ni, 135
Solid solutions, 65, 83–95, 102, 179
interstitial, 84
nonstoichiometric, 83
substitutional, 65
Solidification, nucleation, 70
Solidus curve, 85
Solute, 83, 102
Solvent, 83, 102
Solvation curve, 90
Sound velocity, 347
Space charge layer (SCL), 437, 477. *See also pn junction*
Specific heat capacity, 31, 101
Spectral irradiance, 202
Spherical harmonic, 232
Spin, 245–247
of an electron (defined), 271
magnetic moment, 280
magnetic quantum number, 246
paired, 255
Stern-Gerlach experiment, 250
Spin-orbit coupling, 280–281
potential energy, 281
Spontaneous emission, 259, 271
Spattering, 167
SQUID, 731
State, electronic, 234, 247, 271, 365
ground, 215
stationary state, 210
Statistics, 312–315
Boltzmann classical statistics, 312–313, 363
Boltzmann tail, 315
Fermi-Dirac statistics, 123, 312–315, 364
of donor occupation, 390, 465
of dopant ionization, 400
Stefan-Boltzmann law. *See Blackbody radiation*
Stefan's black body radiation law, 179, 203–204
Stefan's constant, 203–204
Stimulated emission, 259, 271
Stoichiometric compounds, 75, 102
Stoichiometry, 75–76
Stokes' shift, 872, 844
Strain, 24, 102
shear strain, 102
volume strain, 102
Strain gauge, 186
Stress, 24, 102
shear stress, 102
Strong force, 4
Substrate, 544, 572
Superconducting solenoid, 737–739, 771
Superconductivity, 685, 729–740, 763
critical current, 736–739, 769
critical magnetic field, 735, 760
critical surface, 737
critical temperature, 729, 760
high T_c materials, 731, 736
Meissner effect, 729–733, 762
Meissner state, 734
origin, 739–740
penetration depth, 734
table, 736
type I and II, 733–736, 763
vortex state, 735
weak link, 757
zero resistance, 729–733
Supercold liquid, 78
Surface current, 690
Surface polarization charges, 589
density, 590
Surface scattering, 168
Surface tracking, 628, 672. *See also Dielectric breakdown*
Temperature coefficient of capacitance (TCC), 672, 677
Temperature coefficient of resistivity (TCR ero), 125–134, 180, 182
definition, 128
metals (table), 129

- Temperature dependence of resistivity in pure metals, 122-125
 Temperature of light bulb filament, 187
 Ternary alloys, 545
 Terrace-lodge-kink model. *See* Kossel model
 Tetragonal crystals, 97
 Thermal coefficient of linear expansion, 33, 102, 187
 Thermal conduction, 149-154, 185
 Thermal conductivity, 149-153, 180
 Ag, 183
 due to photons, 348
 graph (versus electrical conductivity), 150
 of nonmetals, 348-350
 table, 152
 Thermal equilibrium, 40
 Thermal equilibrium carrier concentration, 397, 464
 Thermal evaporation, 167
 Thermal expansion, 31-36, 102
 Thermal expansion coefficient. *See*
 Thermal coefficient of linear expansion
 Thermal fluctuations, 40-45
 Thermal generation, 376
 Thermal generation current, 572-573
 Thermal radiation, 202. *See also* Blackbody radiation
 Thermal resistance, 153-154, 180, 185
 Thermal velocity, 40, 387, 401, 464
 Thermalization, 427
 Thermally activated conductivity, 161, 179
 Thermally activated processes, 45-49, 161
 activated state and activation energy, 46, 161
 Arrhenius type behavior, 45
 diffusion, 46
 diffusion coefficient, 48
 jump frequency, 47
 root mean square displacement, 48
 Thermionic emission, 328-332, 365, 369
 constant, 331
 Thermocouple, 322-328
 equation, 325, 327-328, 369
 Thermoelectric cooler, 443-448
 Thermoelectric conf., 325, 327
 metals (table), 326
 Thermoelectric power, 322-323
 Thin film, 180, 188
 Thin film head, 252
 Thin metal films, 166-172
 Threshold voltage, 539-541, 573
 Toroid, 693-696, 765
 Total internal reflection (TIR), 789-792, 797, 844
 critical angle, 791, 842
 phase change in, 797
 Transducer. *See* Piezoelectric transducer
 Transistor action, defined, 509, 573. *See also* Bipolar junction transistor
- Transition temperature, 61
 Transmission coefficient, 844
 Transparency, 799-803, 844
 Transverse electric field, 793
 Transverse magnetic field, 793
 Trapping, 409
 Triclinic crystal system, 97
 Tunneling, 221-228, 271, 278
 field-assisted probability, 334
 probability, 223
 reflection coefficient, 223
 scanning tunneling microscope, 223-227
 transmission coefficient, 222-223
 Two-phase alloy resistivity, 143-144
 Ag-Ni, 143
 Two phase solids, 83-95
- Unharmonic effect, 34
 Unharmonic oscillations, 34
 Unharmonicity, 34, 349
 Uniaxial crystals, 828
 Unipolar conductivity, 118
 Unit cell, 50, 56, 97, 102
 hexagonal, 52
 Unpolarized light, 796
 Upper cut-off (threshold) wavelength, 813
 graph, 814
 table, 813
- Vacancy, 64-68, 102, 110
 concentration in Al, 67
 concentration in semiconductor, 67-68
 Vacuum deposition, 106-107
 Vacuum level (energy), 292-295, 464
 Vacuum tubes, 328-337
 rectifier, 329
 saturation current, 329
 Valence band (VB), 301, 374-378, 464
 Valence electrons, 5, 102
 Valency of an atom, 5
 van der Waals bond, 19-20
 water (H_2O), 20
 van der Waals-London force, 19
 Vapor deposition, 167. *See also* Physical vapor deposition
 Varactor diodes, 499
 Varshni equation, 467
 VB. *See* Valence band
 Velocity density (distribution) function, 37
 Vibrational wave, 151
 Virial theorem, 6, 7, 102-103
 Vitreous silica, 78
 Volume expansion, 35
 Volume expansion coefficient, 35
 Vortex state, 735
- Wave, defined, 271-272
 dispersion relation, 364, 666, 842
 electromagnetic (EM), 191
 energy densities in an EM, 787
 equation, 272, 347
- fields in EM, 707
 group velocity, 341
 incident, 793
 lattice, 340
 light waves, 774-776
 longitudinal, 339
 matter waves, 210
 monochromatic plane EM, 774
 phase, 774, 843
 phase velocity, 776, 777, 843
 propagation constant, 774
 reflected, 793
 transmitted, 793
 transverse, 339
 traveling, 792, 774-775
 ultrasonic, 641
 vibration, 151
 Wavefront, 774, 844
 Wavefunction, 208-210
 antisymmetric, 216
 defined, 272
 eigenfunction, 210
 matter waves, 210
 one-electron, 254
 stationary states, 210
 steady state total, 209
 symmetric, 216
 Wavelength, 192, 774, 844. *See also*
 Wavelength
 Wavepacket, 784, 844
 Wavevector (k), defined, 192, 272, 776, 844
 of electron, 272, 450-456
 Weak injection, 425
 Weight fractions, 8-9, 88
 White LED, 820-825
 Wiedemann-Franz-Lorenz's law, 150
 Wien's displacement law, 205, 277
 Work function, 196, 272, 295, 363,
 435-437, 443, 464
 effective, 333
 of a semiconductor, 384
 table, 295, 369, 470
- X-rays, 193-194, 199-202, 272, 275-276,
 367, 448
 diffraction, 849-852
 energy fluorescence, 275
 photo fluorescence, 276
 radiography, 275
 sources, 275
- Young's double-slit experiment (figure), 193, 205
 Young's fringes, 192
 Young's modulus, 102. *See also* Elastic modulus
- Zener breakdown, 502-506, 573
 Zener effect, 805
 Zero resistance, 729-733
 Zero-point energy, 365
 Zone refining, 83-90

"We have a habit in writing articles published in scientific journals to make the work as finished as possible, to cover up all the tracks, to not worry about the blind alleys or describe how you had the wrong idea first, and so on. So there isn't any place to publish, in a dignified manner, what you actually did in order to get to do the work."

Richard P. Feynman
Nobel Lecture, 1966